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# Recent Developments in CMOS RF Integrated Circuits

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# Introduction

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- ❑ **Digital CMOS is hardly the ideal medium for RF ICs. But is it hopelessly inferior?**
- ❑ **Interesting question: How well can one do in such a technology if one tries very hard?**
  - ❑ **Scaling delivers faster devices every year; eventually, they'll be fast enough.**
  - ❑ **Is the substrate really so big a problem that good inductors (and capacitors) simply cannot be realized?**
  - ❑ **Is device noise so large that CMOS LNAs will always be HNAs?**
  - ❑ **Does the inferior  $1/f$  noise of CMOS transistors doom the close-in phase noise performance of oscillators?**
- ❑ **Can you *really* build credible RF ICs in standard digital CMOS?**

# Outline

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- ❑ **A few brief words on scaling trends**
- ❑ **The patterned ground shield spiral inductor**
- ❑ **Capacitors**
  - ❑ **Fractal capacitors**
  - ❑ **Accumulation mode varactors**
- ❑ **Passive mixers**
- ❑ **Broadband noise models for the deep submicron regime**
- ❑ **Power-constrained LNA design**
- ❑ **A new phase noise theory and its implications for 1/f noise upconversion**
- ❑ **Putting it all together: A 115mW single chip GPS receiver in 0.5 $\mu$ m CMOS**

# Scaling Trends in Brief

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- ❑ CMOS  $f_T$  (and  $f_{\max}$ ) are in the range of 30GHz now, and double roughly every three years.
- ❑ Devices with  $\sim 75\text{nm}$   $L_{\text{eff}}$  have been demonstrated, and exhibit  $\sim 150\text{GHz}$   $f_T$ !
- ❑ CMOS suffers from large source/drain parasitics, compared with other technologies.
  - ❑ Gate-drain “overlap” capacitance is also large.
- ❑ Series gate resistance is also an increasingly serious problem as gate lengths continue to shrink, but can be accommodated by using narrower unit devices.
  - ❑ Salicided gates help, too.
- ❑ Interconnect layers increasing at  $\sim 0.75$  to 1 level per generation (5 layers are now relatively common).

# Passive Elements: Planar Spiral Inductors

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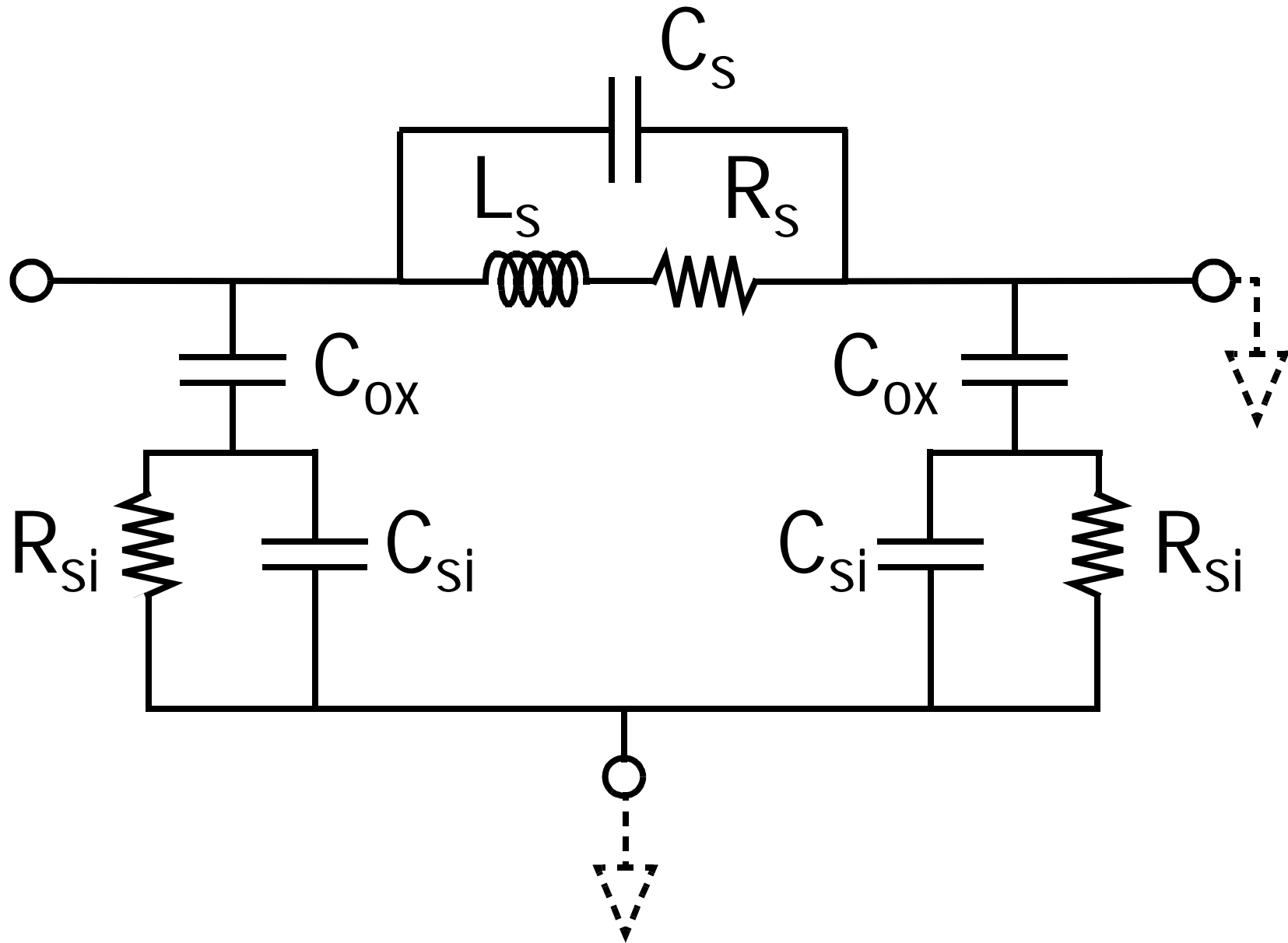
- ❑ Planar spirals in Si technology are infamous for poor  $Q$  (typically well below 10).
- ❑ Conductor resistance, exacerbated by skin and proximity effects, typically accounts for about half the loss.
  - ❑ Applies to both bulk and epi technologies.
- ❑ The remaining loss is primarily due to currents flowing in the substrate.
  - ❑ Getting rid of the substrate would work wonders (e.g., post-fab etch, SOA, etc.), but requires deviation from ordinary process technology.
  - ❑ Next-best choice is to use a high-resistivity substrate, but can't do so without sacrificing other CMOS characteristics.
  - ❑ Next next-best choice is to construct a *pseudo-substrate* out of existing interconnect layers.

# Passive Elements: Planar Spiral Inductors

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- ❑ **Most of the substrate loss is *not* due to the flow of magnetically induced eddy currents, contrary to widespread superstition.**
- ❑ **Main mechanism is simply current flow into the substrate through the parasitic capacitance between inductor and substrate.**
- ❑ **Grounded shield interposed between inductor and substrate diverts this current into ground.**
  - ❑ **Slots cut into ground shield prevent loss in shield due to eddy currents.**
  - ❑ **Drawback is a reduction in self-resonant frequency due to increase in parasitic capacitance (can mitigate this by using higher-level metal layers).**

# Model Description

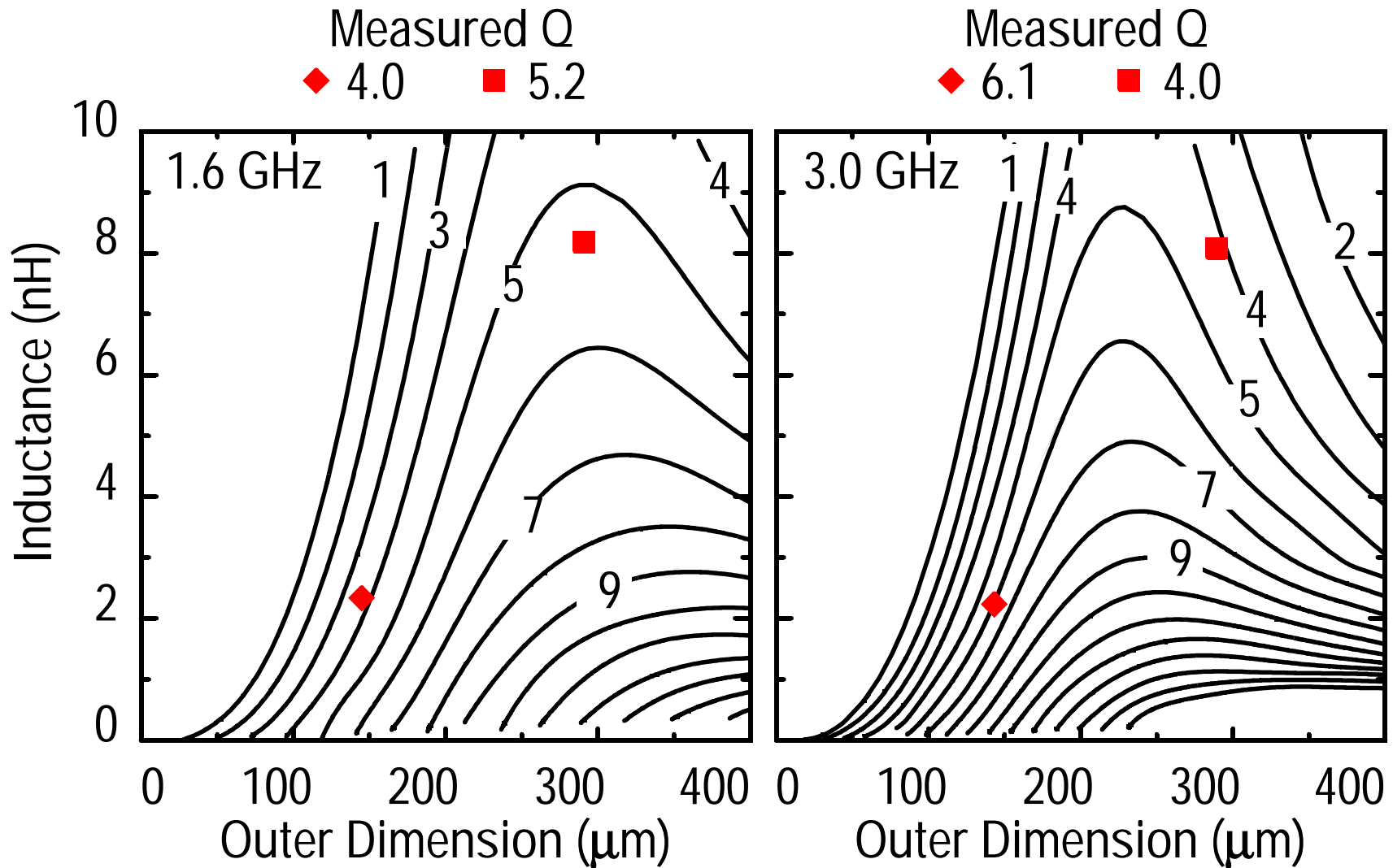


# Model Description

Physical Model of Inductor on Silicon		Effects
	$L_s$ : Greenhouse Method	Mutual Couplings
	$R_s = \frac{\rho \cdot l}{w \cdot \delta \cdot (1 - e^{-t/\delta})}$	Eddy Current
	$C_s = n \cdot w^2 \cdot \frac{\epsilon_{ox}}{t_{ox} M1-M2}$	Feed-Through Capacitance
	$C_{ox} = \frac{1}{2} \cdot l \cdot w \cdot \frac{\epsilon_{ox}}{t_{ox}}$	Oxide Capacitance
	$C_{si} = \frac{1}{2} \cdot l \cdot w \cdot C_{Sub}$	Si Substrate Capacitance
	$R_{si} = \frac{2}{l \cdot w \cdot G_{Sub}}$	Si Substrate Ohmic Loss

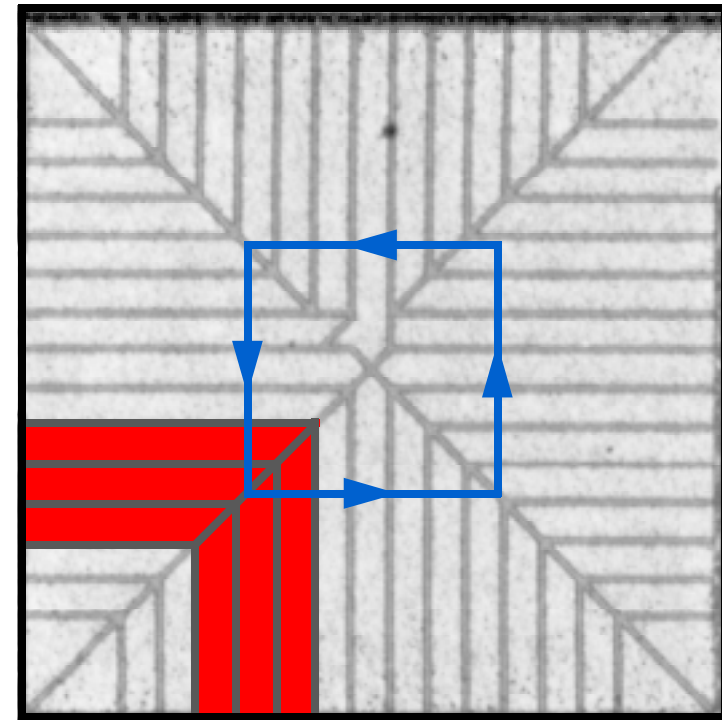


# Contour Plots of Q



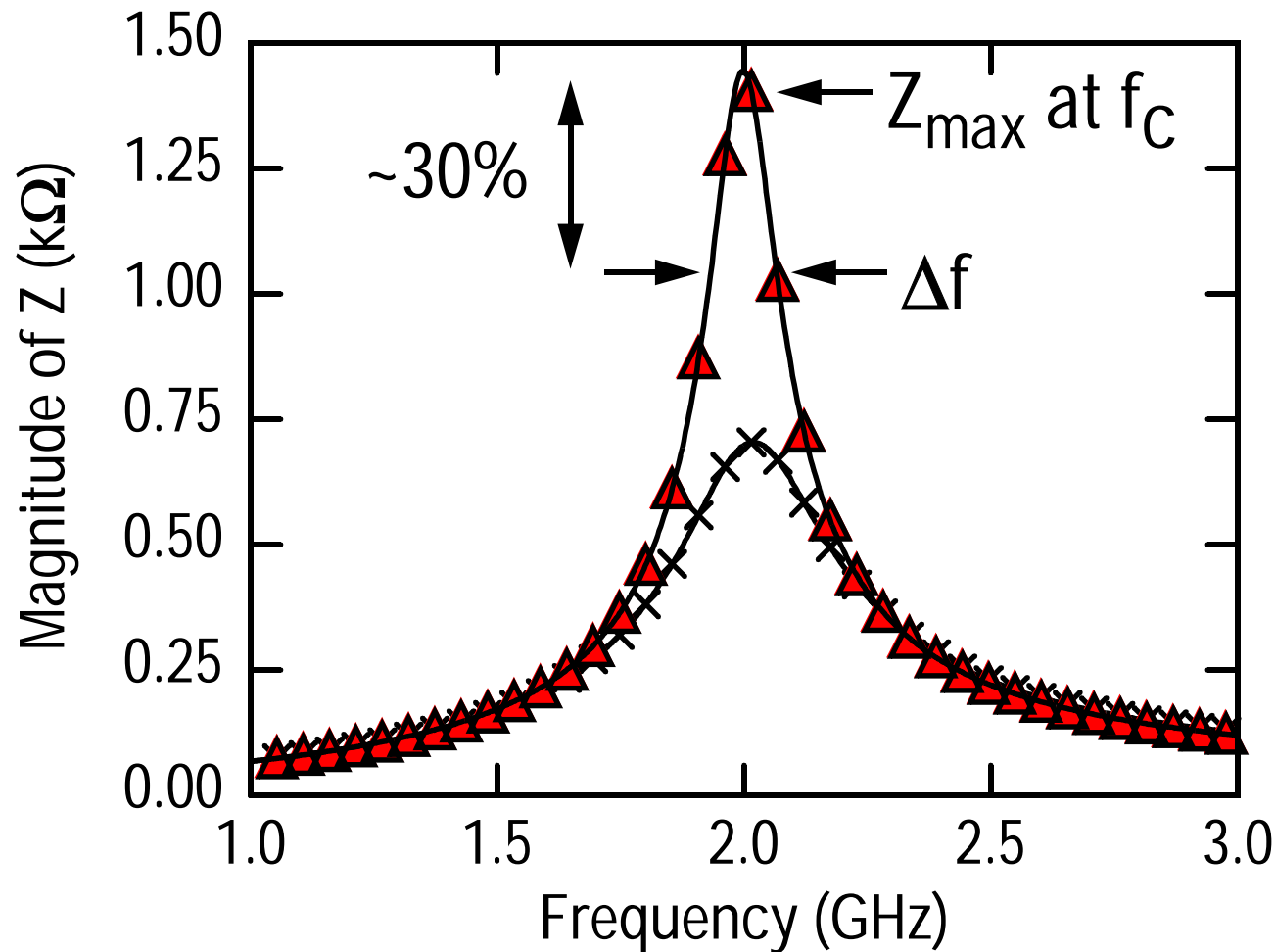
# Patterned Ground Shield Design

- Pattern
  - Orthogonal to spiral  
(induced loop current)
- Resistance
  - Low for termination of  
the electric field
  - Avoid attenuation of  
the magnetic field

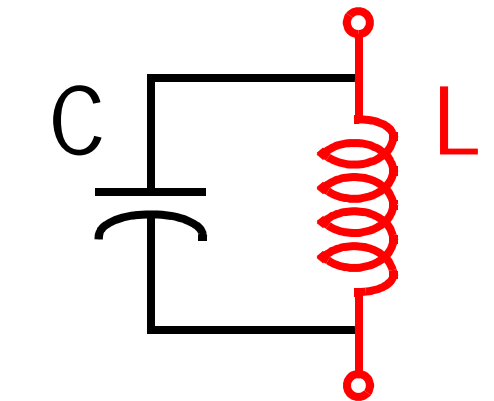






- Ground Strips
- Slot between Strips
- Induced Loop Current

# Parallel LC Resonator at 2 GHz

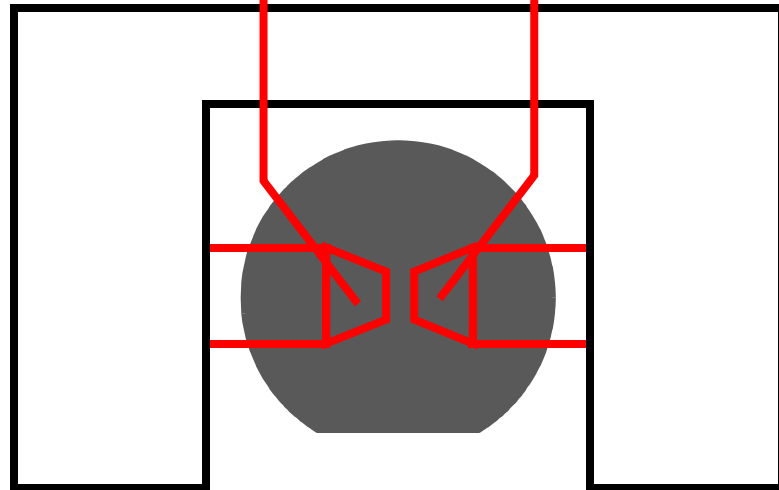
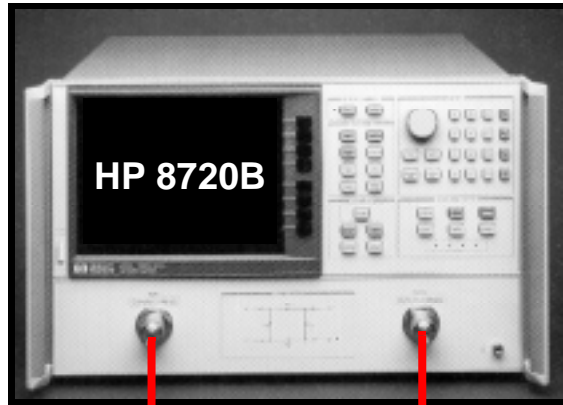


$$Q_{\text{RESONATOR}} = \frac{f_c}{\Delta f}$$

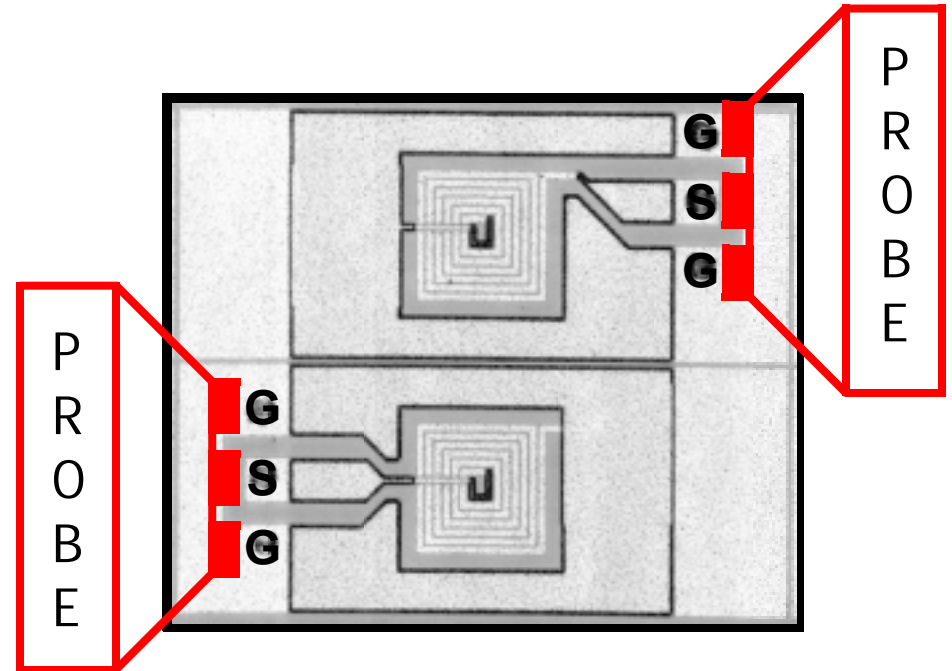


-   Patterned Polysilicon
-   None (11  $\Omega$ -cm)

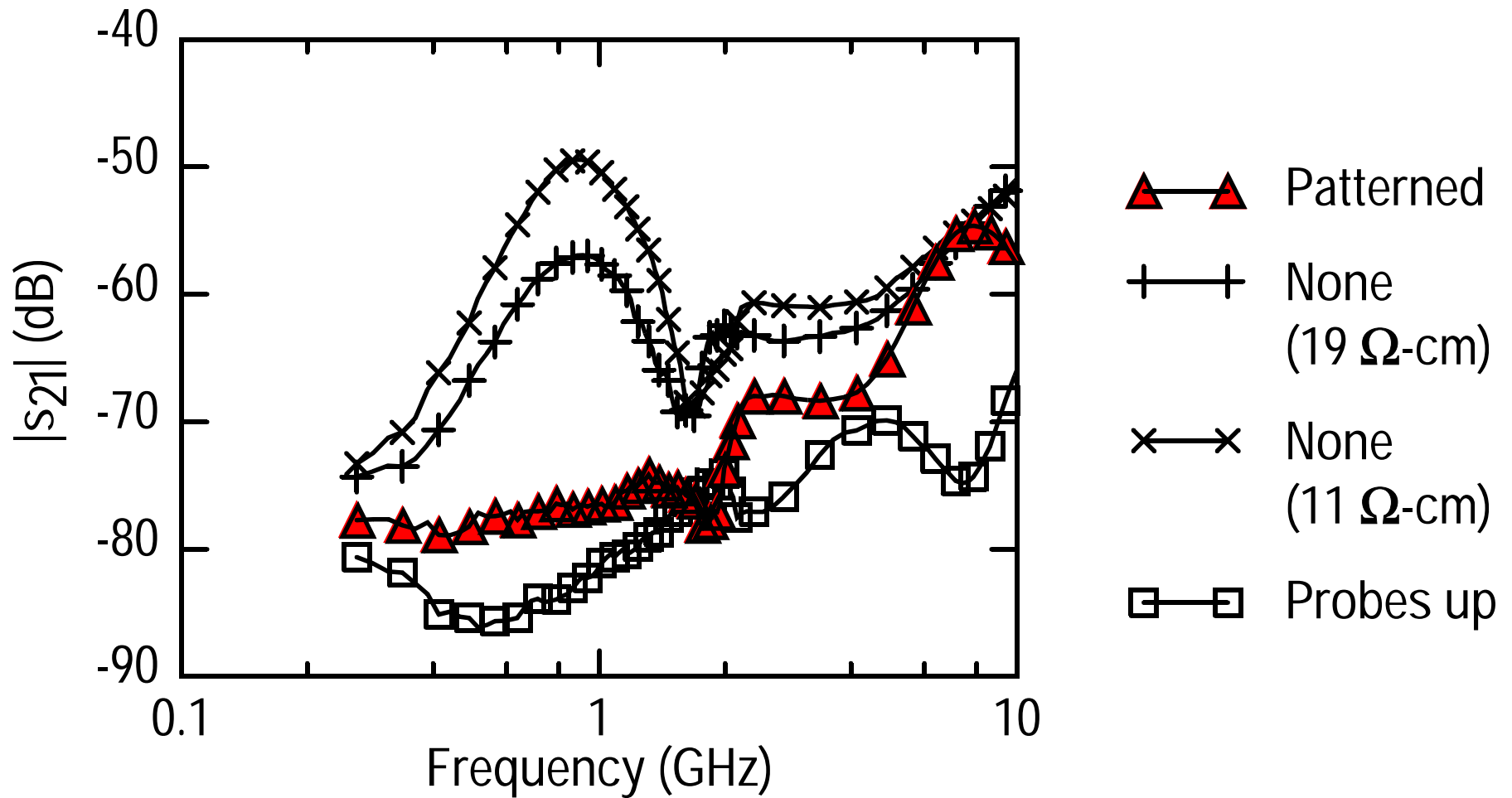
# Noise Coupling Measurement



Probe Station



# Effect of Polysilicon GS on Isolation



# Passive Elements: Capacitors

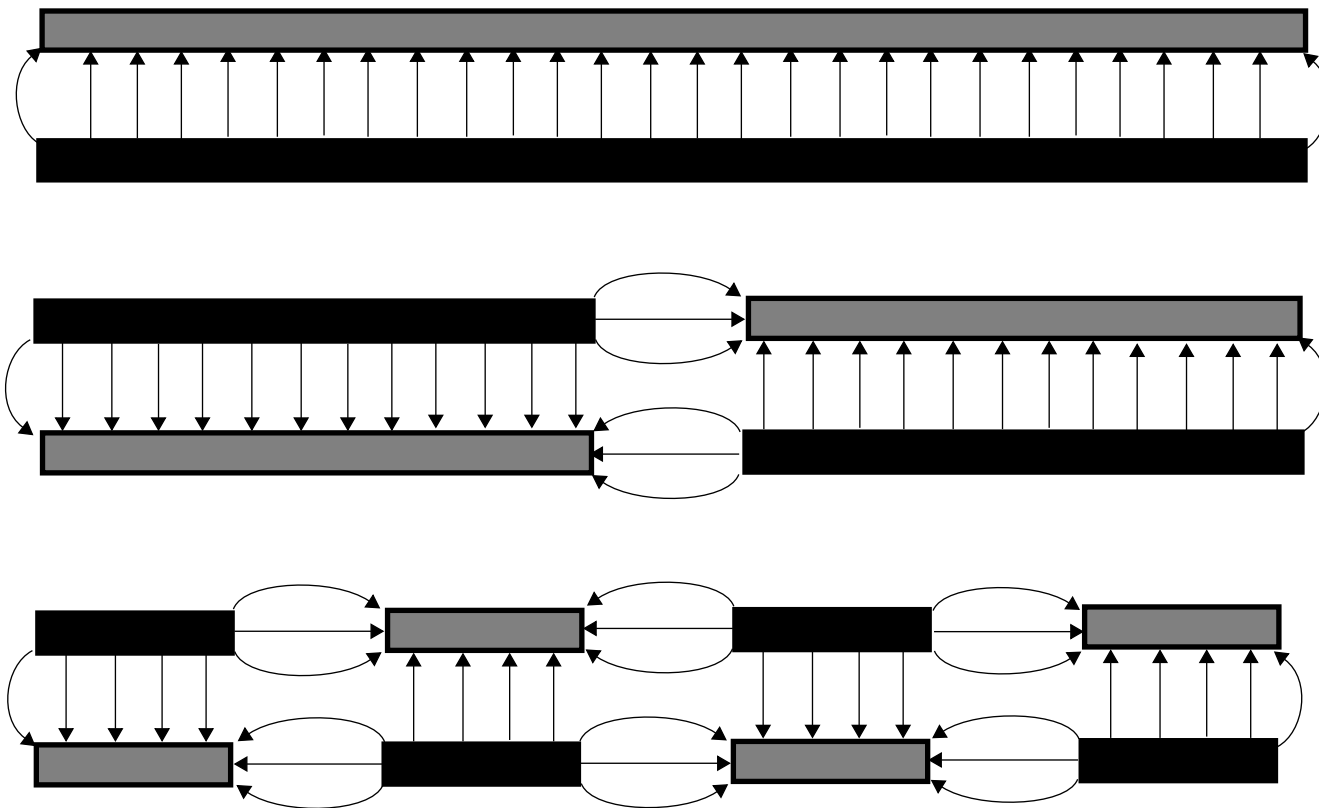
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- ❑ Ordinary parallel plate structures don't scale with technology because the vertical spacing is held roughly constant to keep interconnect capacitance small.
- ❑ Bottom-plate parasitics are large (e.g., 30% of main capacitance).
- ❑ Gate capacitors are area efficient, but impose bias constraints, and are not as linear as MIM structures.
- ❑ Traditional varactor options (e.g., p+ in n-well) have poor Q
  - ❑ Gate capacitors in accumulation-mode are an attractive alternative (Q values in excess of 100 at 1GHz are potentially realizable)

# Vertical vs. Lateral Flux

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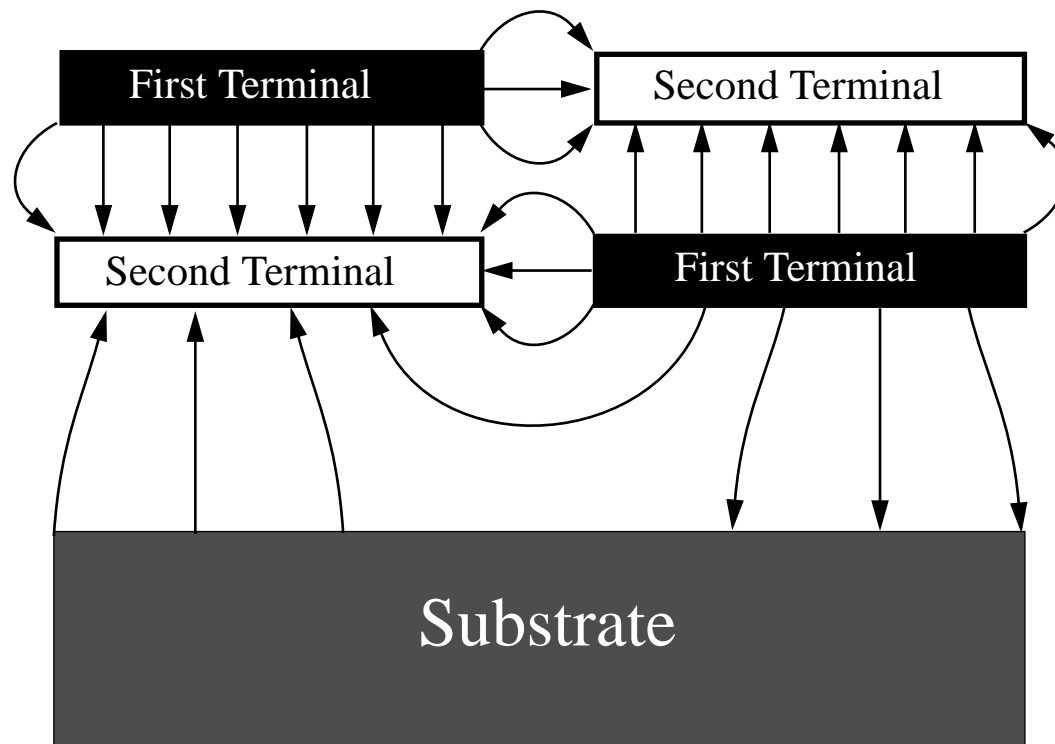
- Lateral flux increases the total amount of capacitance.



# Reduction of the Bottom-Plate Capacitance

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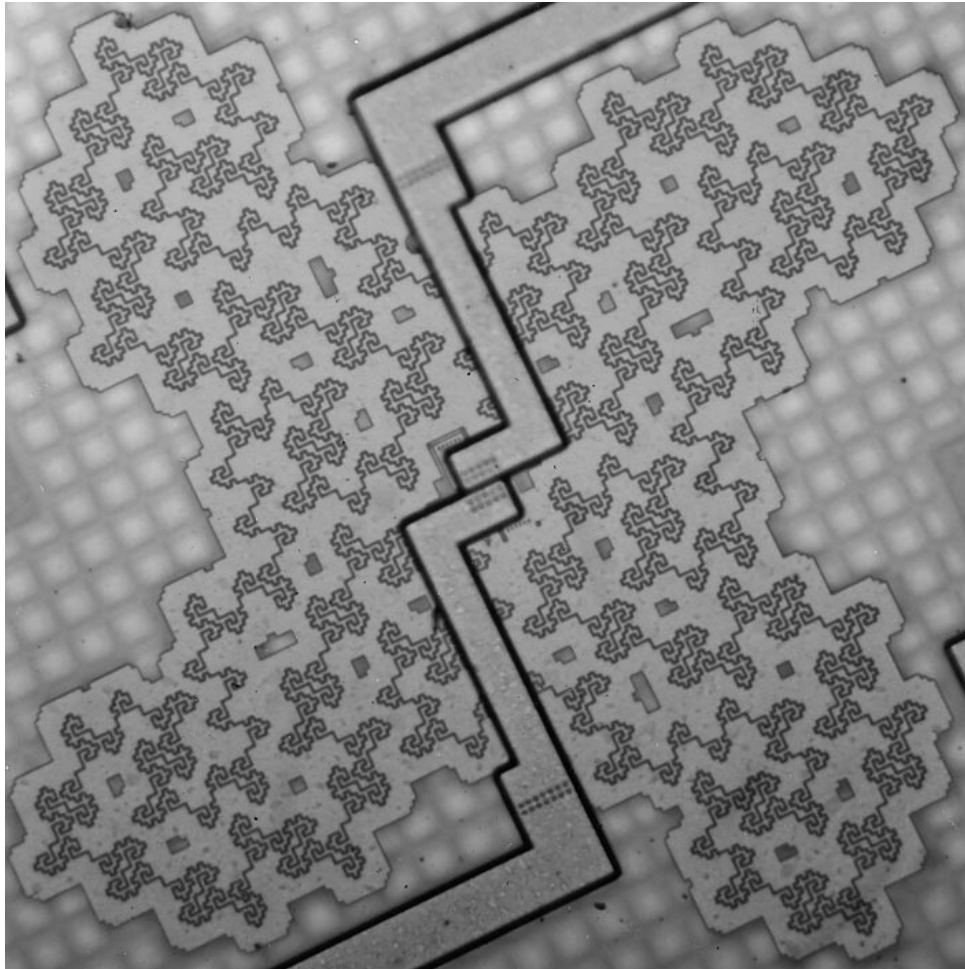
- Area is smaller.
- Some of the field lines terminate on the adjacent plate instead of the substrate.





# Die Micrograph

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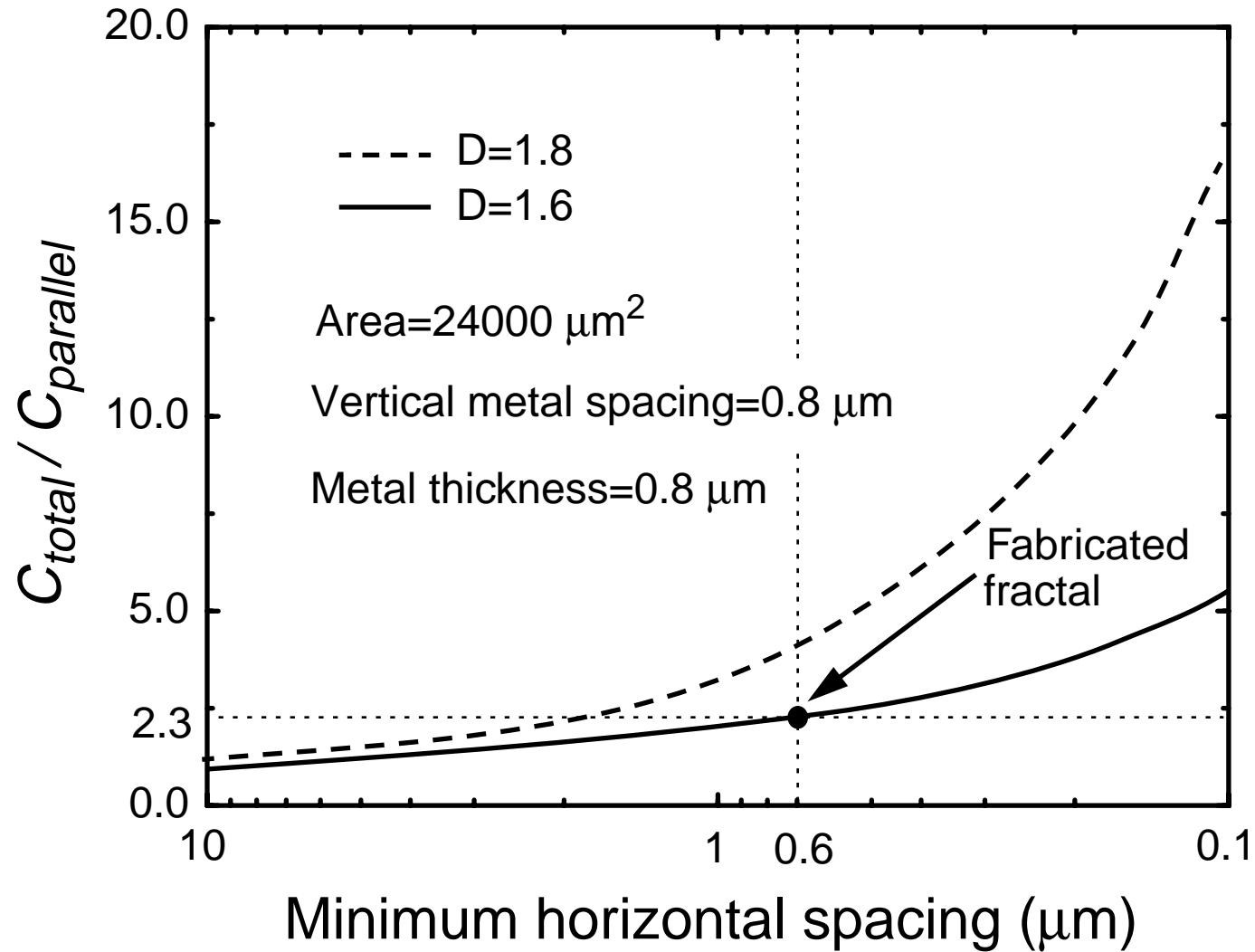


Horizontal spacing= $0.6 \mu\text{m}$

Vertical spacing= $0.8 \mu\text{m}$

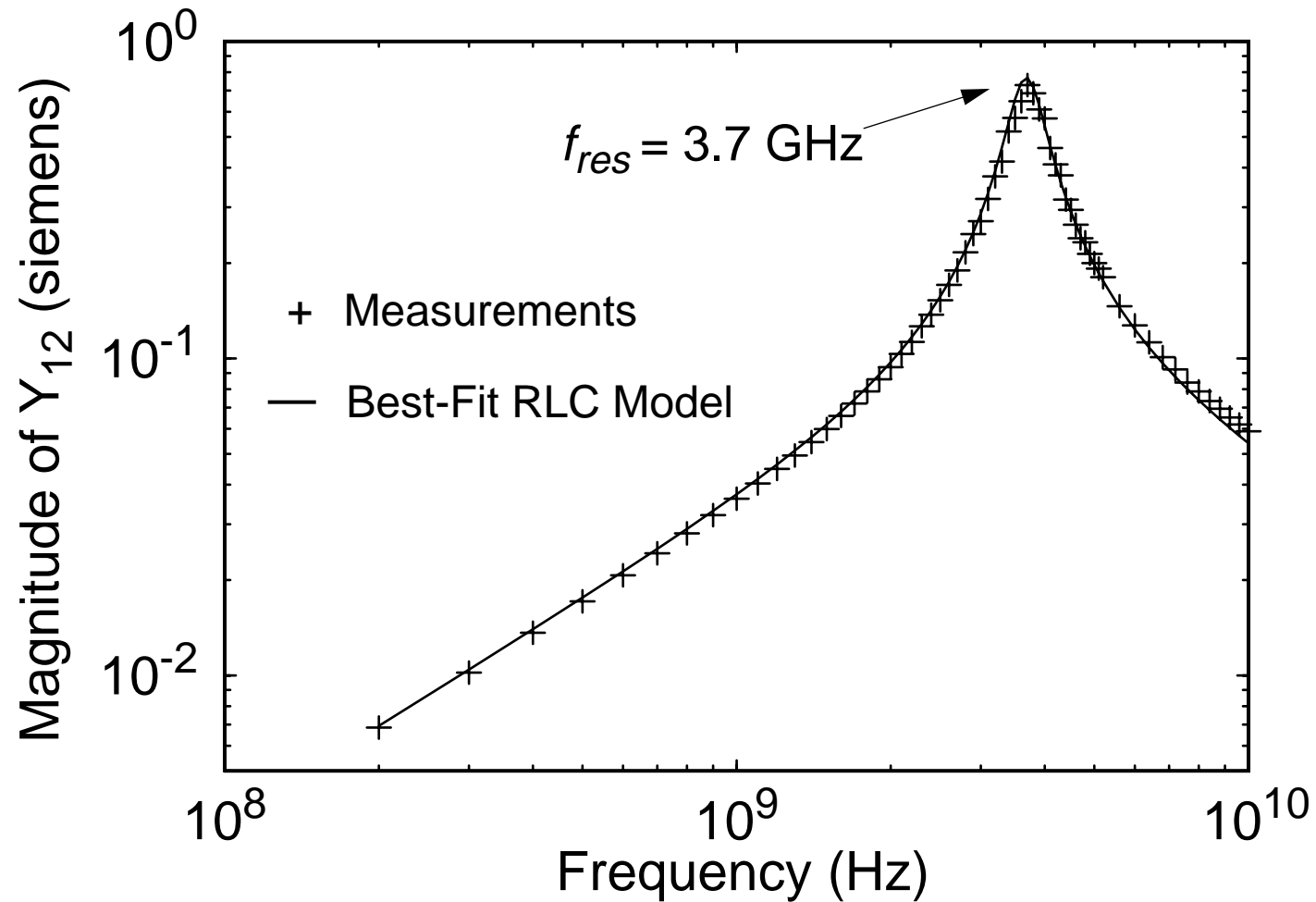
Area= $24,000 \mu\text{m}^2$

# Boost Factor vs. Lateral Spacing



# Measurements

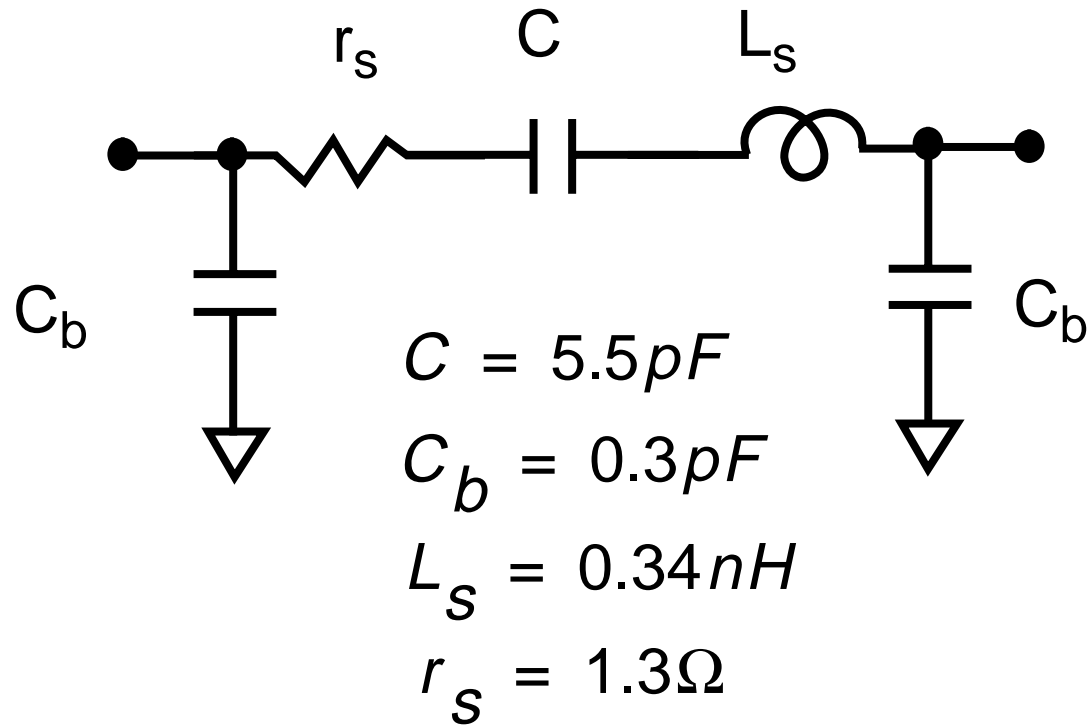
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High-frequency two-port measurements

# Measurements

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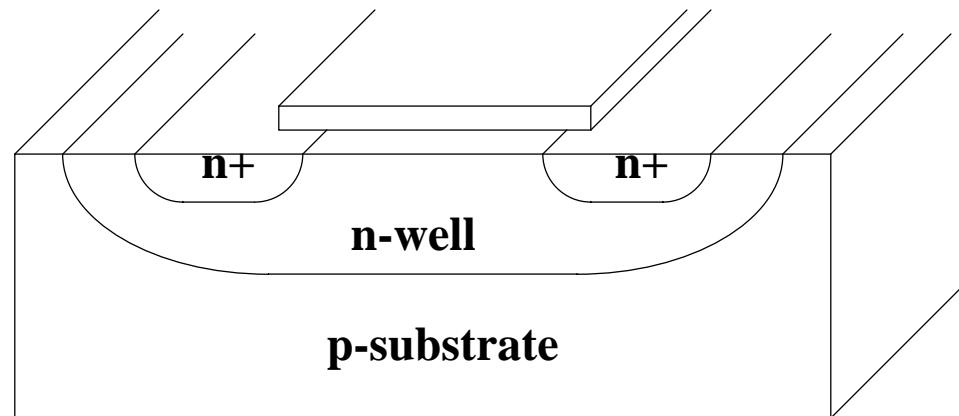


Best-Fit Parameters

# Passive Elements: Capacitors

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- ❑ **Accumulation-mode varactor (ref. Soorapanth et al., VLSI Circuits Symposium, June 1998):**

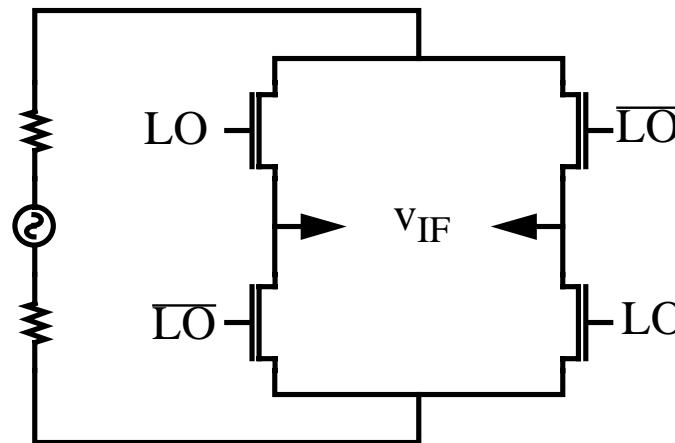


- ❑ **Compatible with standard CMOS processing**
- ❑ **Practical capacitance range exceeds 150%**

# Passive Mixers

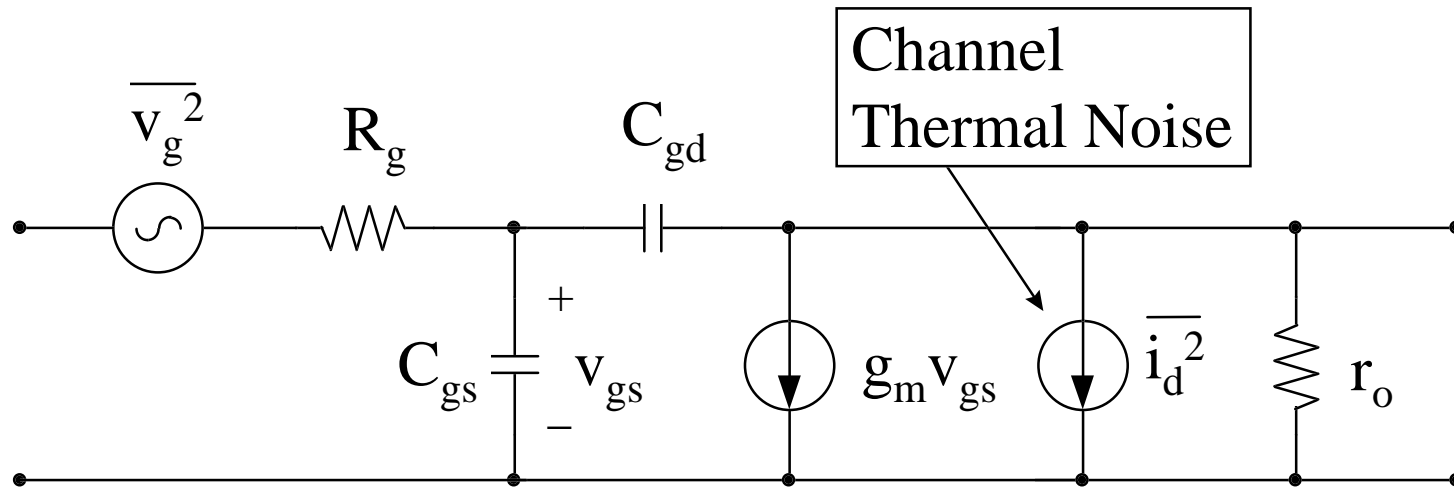
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- ❑ Gilbert multiplier performs mixing in current domain because bipolar transistors are not good voltage switches.
- ❑ Penalty: V-I conversion costs power and linearity
- ❑ CMOS voltage switches are excellent, so mixers made out of them work well:



- ❑ @1.6GHz: 3.6dB loss, +10dBm IIP3 achieved at 200 $\mu$ W

# Simple CMOS Noise Model



- Channel thermal noise is dominant.

$$\overline{i_d^2} = 4kTB\gamma g_{d0}$$

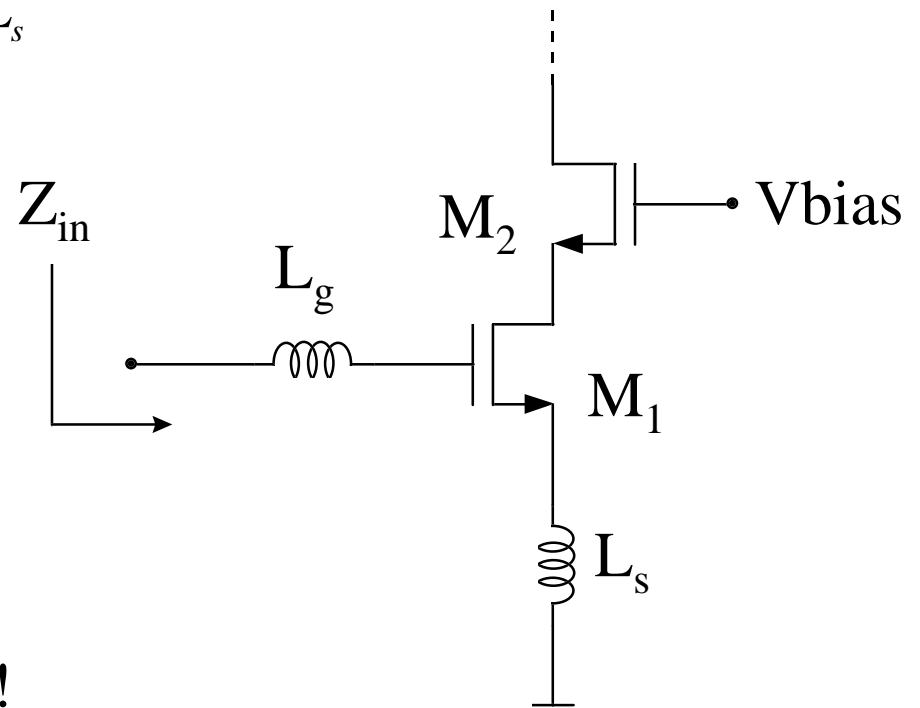
- Gate resistance minimized by good layout.

# LNA Input Stage

$$Z_{in} = s(L_s + L_g) + \frac{1}{sC_{gs}} + \left(\frac{g_m}{C_{gs}}\right)L_s \approx \omega_T L_s$$

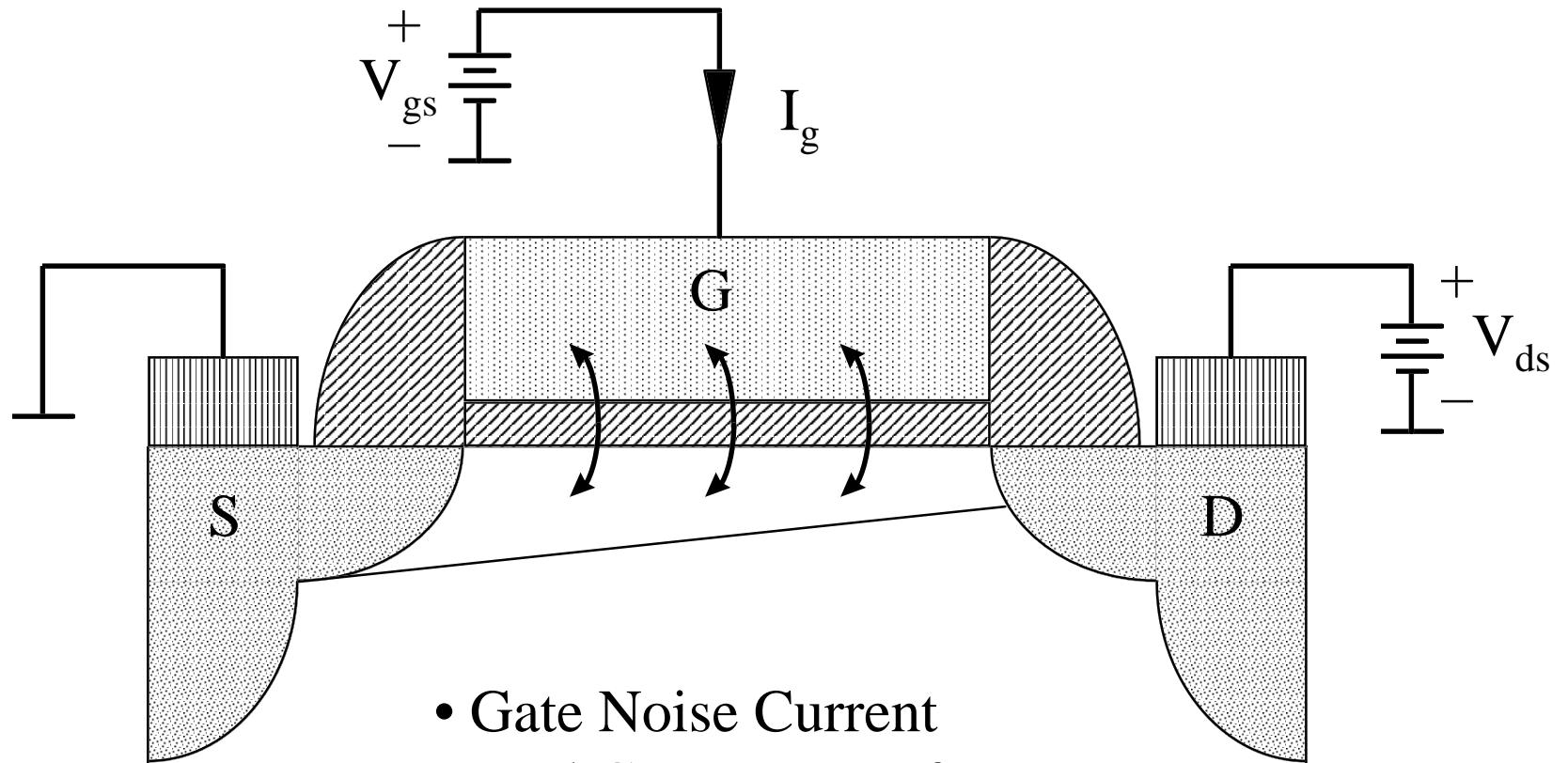
$$\begin{aligned} G_{m,eff} &= g_{m1} Q_{in} = \frac{g_{m1}}{\omega C_{gs} (R_s + \omega_T L_s)} \\ &= \frac{\omega_T}{\omega R_s \left(1 + \frac{\omega_T L_s}{R_s}\right)} = \frac{\omega_T}{2\omega R_s} \end{aligned}$$

Note:  $G_{m,eff}$  is independent of  $g_{m1}$ !





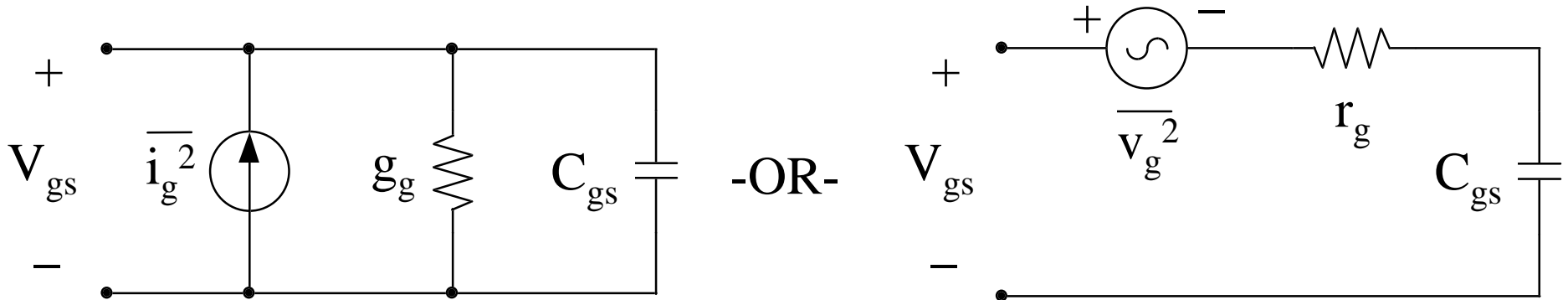
# Induced Gate Effects



- Gate Noise Current
- Real Component of  $Z_g$



# Equivalent Gate Circuit



$$\overline{i_g^2} = 4kTB\delta g_g \quad g_g = \frac{1}{5} \frac{\omega^2 C_{gs}^2}{g_{d0}}$$

$$\overline{v_g^2} = 4kTB\delta r_g \quad r_g = \frac{1}{5g_{d0}}$$

“Blue” Noise

- $\delta$  ( $\sim 4/3$ ) modified by hot electron effects
- $\overline{i_g^2}$  partially correlated with  $\overline{i_d^2}$  ( $c = 0.395j$ )
- $\overline{i_g^2}$  and  $g_g$  not modeled in HSPICE

“White” Noise



# LNA Design Procedure

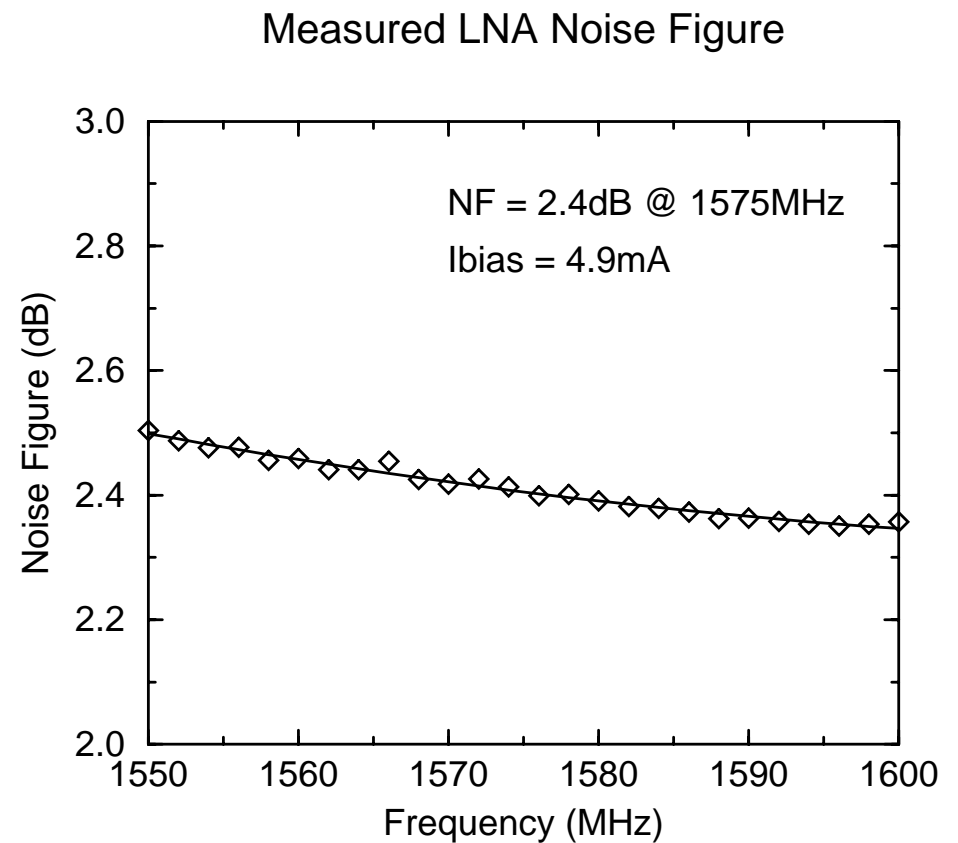
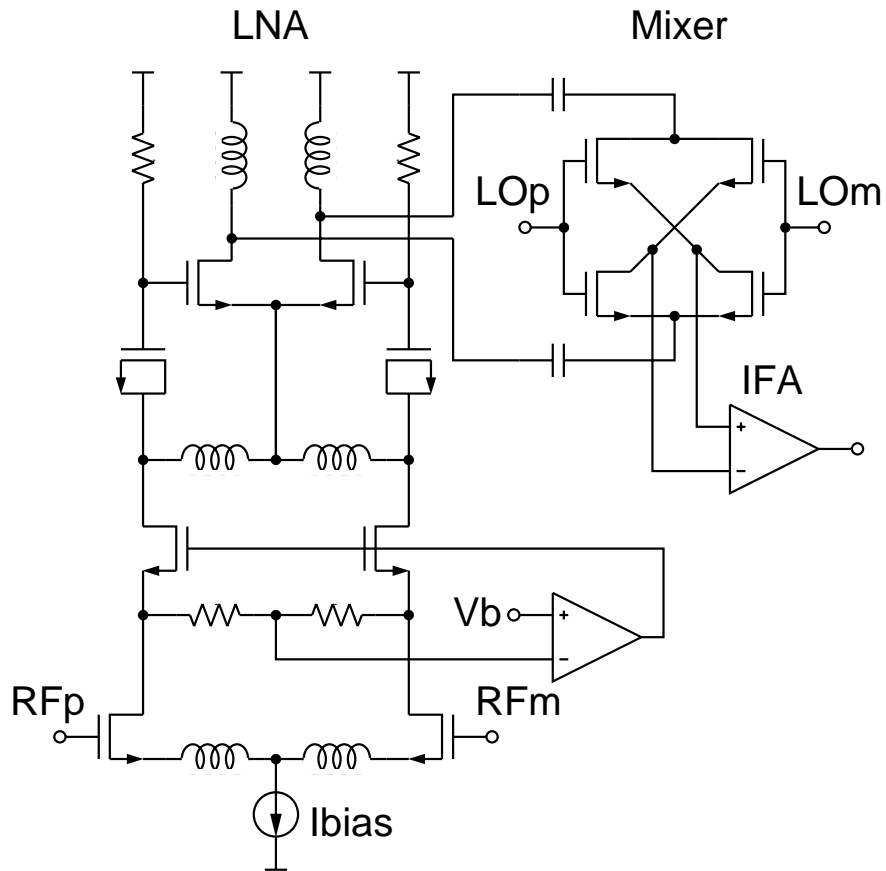
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- ❑ **Select device width roughly equal to  $(500\mu\text{m}\cdot\text{GHz})/f_0$  (for a  $50\Omega$  system)**
- ❑ **Adjust bias to obtain desired power dissipation**
  - ❑ **Keep  $V_{DS}-V_{DSAT}$  as small as practical to minimize hot-electron effects (say, under half a volt or so)**
- ❑ **Select source degeneration inductance (assuming equal-sized cascoding and main devices) according to:**

$$L_S \approx \frac{R_S \cdot [1 + 2(C_{gd}/C_{gs})]}{\omega_T}$$

- ❑ **Add enough gate inductance to bring input to resonance**
- ❑ **Noise factor bound is  $1 + 2.4(\gamma/\alpha)(\omega/\omega_T)$ , so scaling continues to help directly**

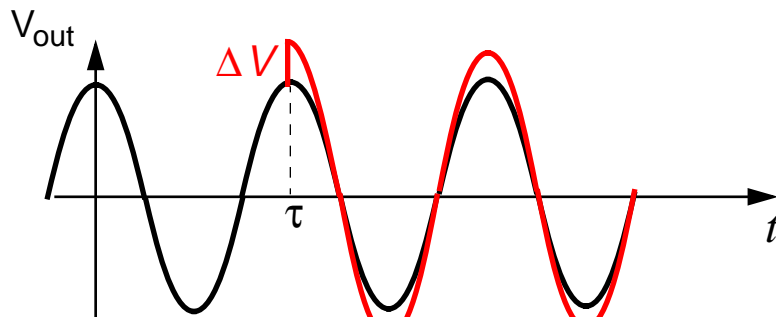
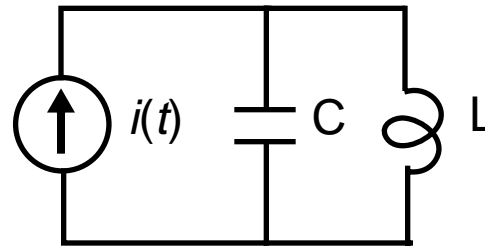
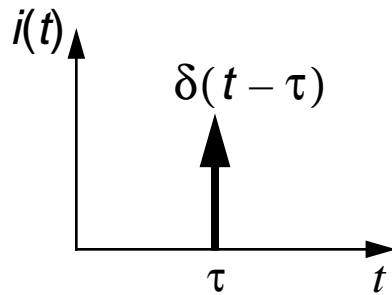
# CIRCUITS: LNA / MIXER



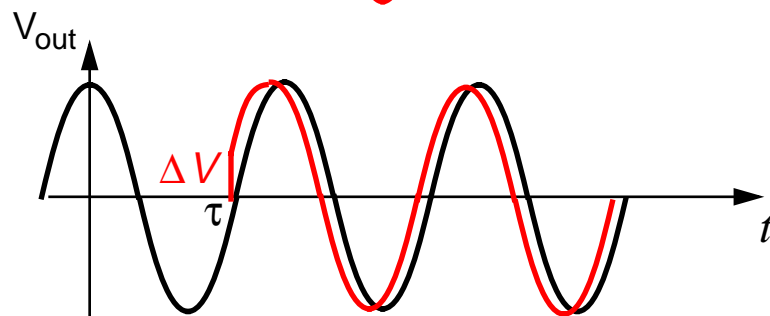
Shahani, Shaeffer and Lee, "A 12mW Wide Dynamic Range CMOS GPS Receiver," ISSCC 1997

# Oscillators Are Time-Variant Systems

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Impulse injected at the peak of amplitude.

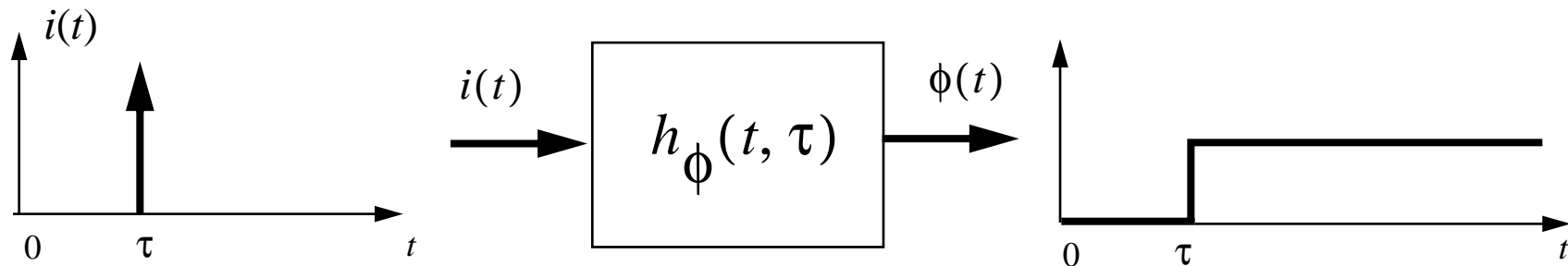


Impulse injected at zero crossing.

Even for an ideal LC oscillator, the phase response is *Time Variant*.

# Phase Impulse Response

*The phase impulse response of an arbitrary oscillator is a time varying step.*



The unit impulse response is:

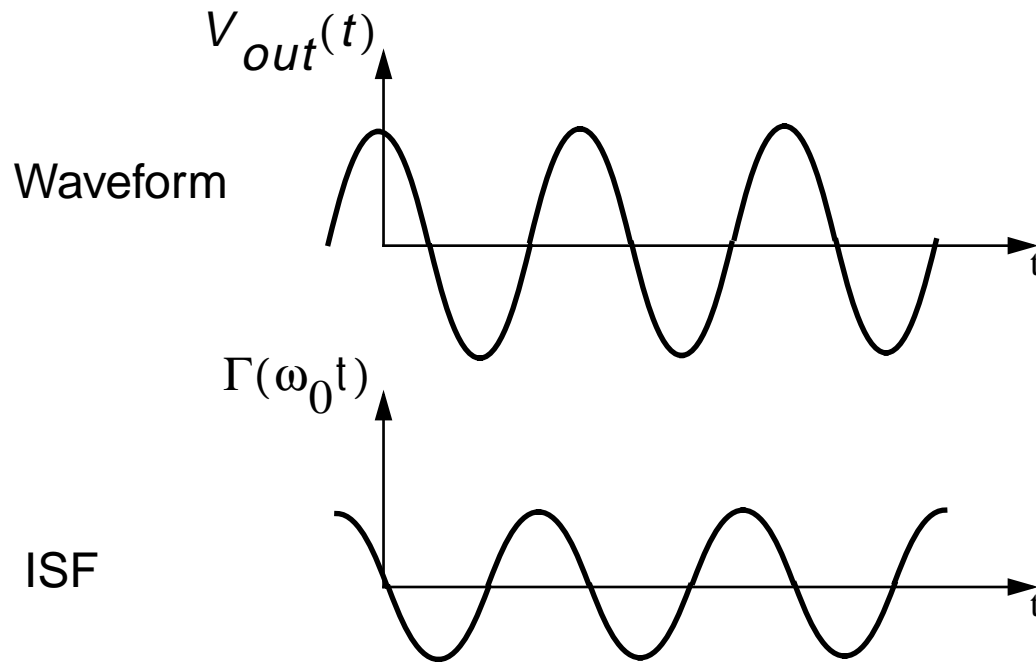
$$h_{\phi}(t, \tau) = \frac{\Gamma(\omega_o \tau)}{q_{max}} u(t - \tau)$$

$\Gamma(x)$  is a dimensionless function periodic in  $2\pi$ , describing how much phase change results from applying an impulse at time:  $t = T \frac{x}{2\pi}$

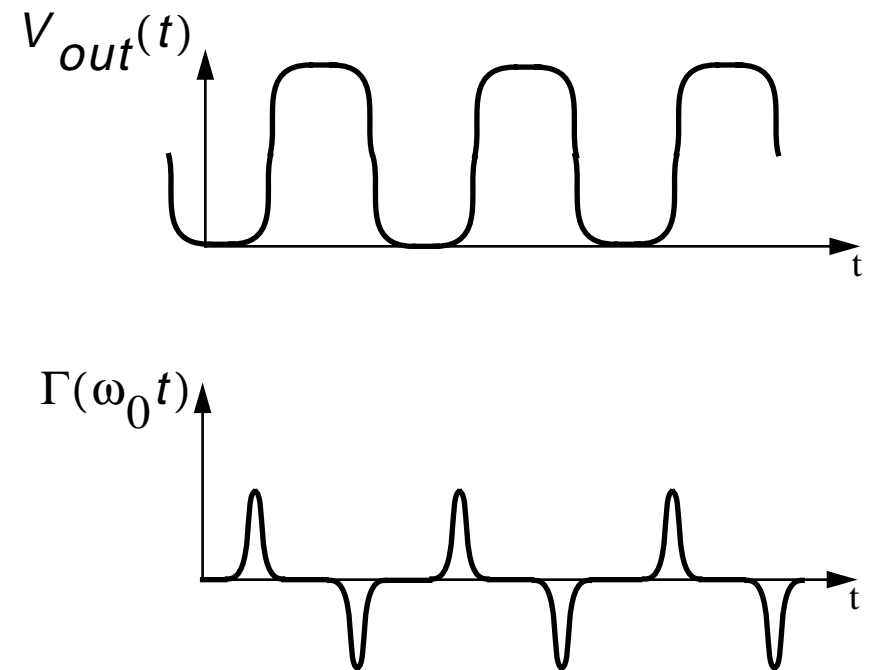
# Impulse Sensitivity Function (ISF)

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LC Oscillator

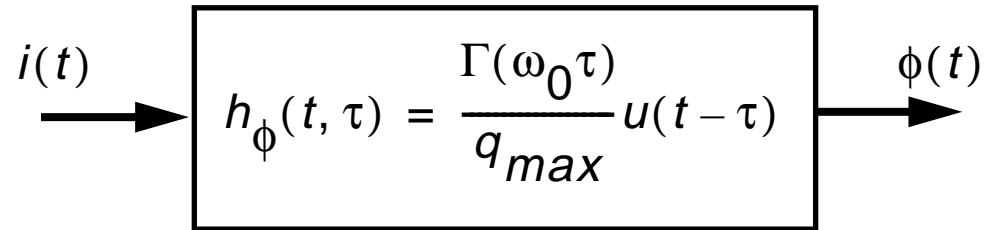


Ring Oscillator



*The ISF quantifies the sensitivity of every point in the waveform to perturbations.*

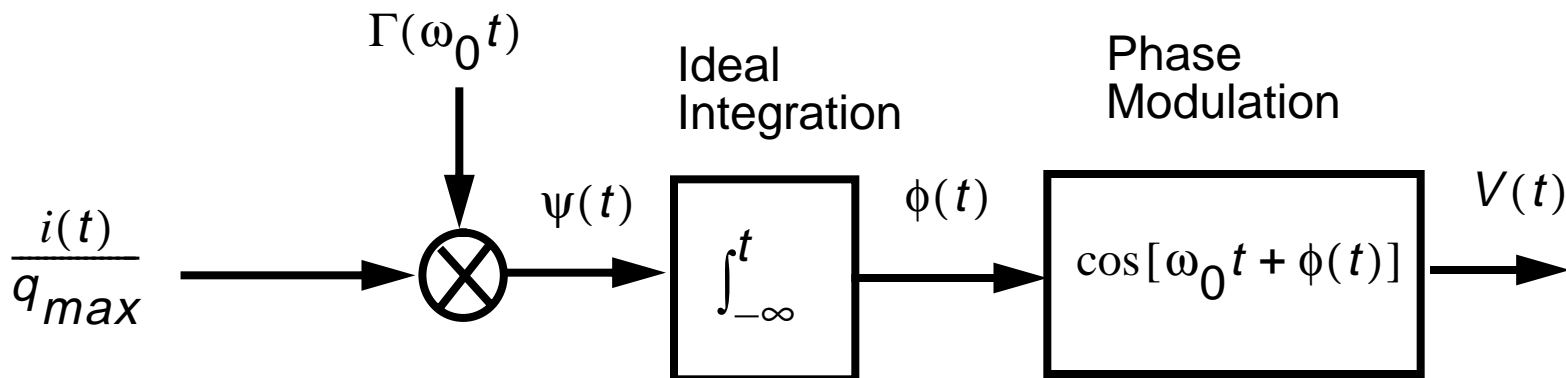
# Phase Response to an Arbitrary Source



Superposition Integral:

$$\phi(t) = \int_{-\infty}^{\infty} h_{\phi}(t, \tau) i(\tau) d\tau = \frac{1}{q_{max}} \int_{-\infty}^t \Gamma(\omega_0 \tau) i(\tau) d\tau$$

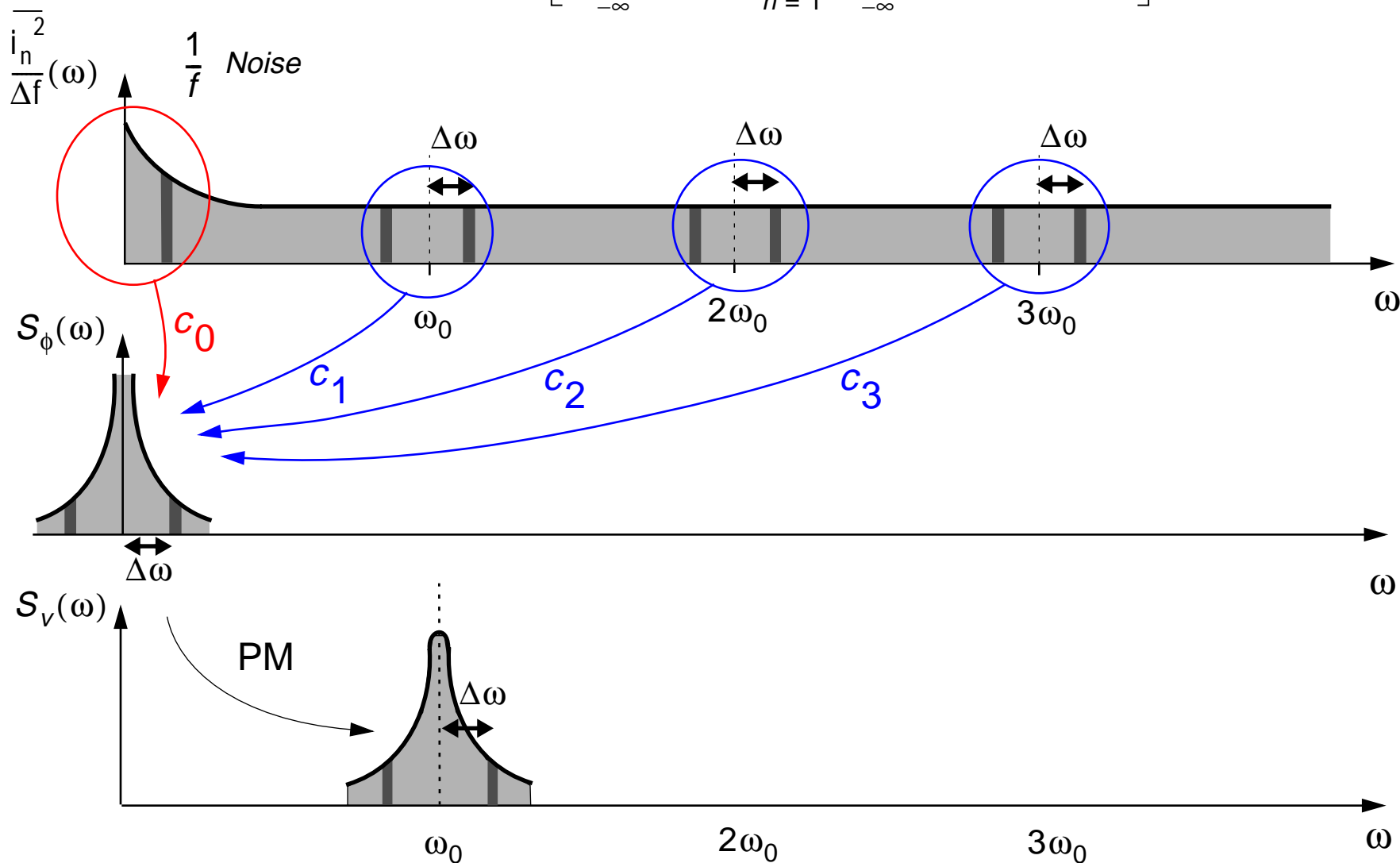
Equivalent representation:





# Noise Contributions from $n\omega_0$

$$\phi(t) = \frac{1}{q_{max}} \left[ c_0 \int_{-\infty}^t i(\tau) d\tau + \sum_{n=1}^{\infty} c_n \int_{-\infty}^t i(\tau) \cos(n\omega\tau) d\tau \right]$$



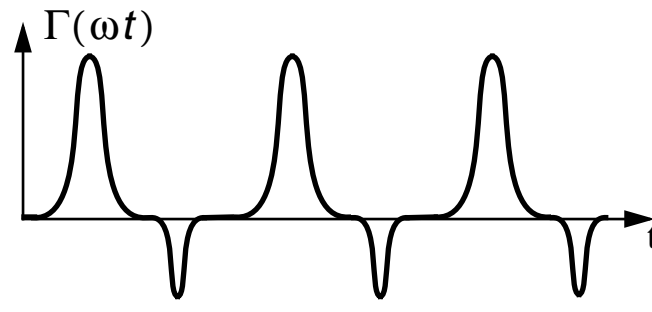
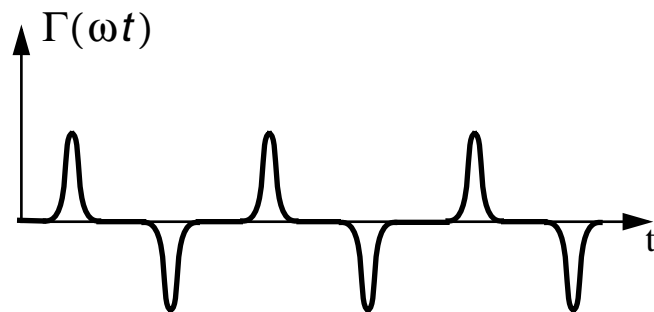
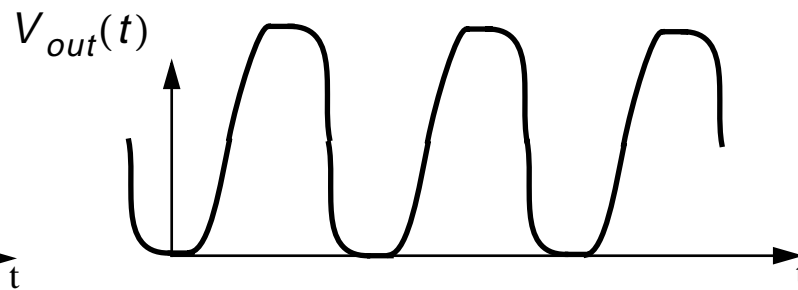
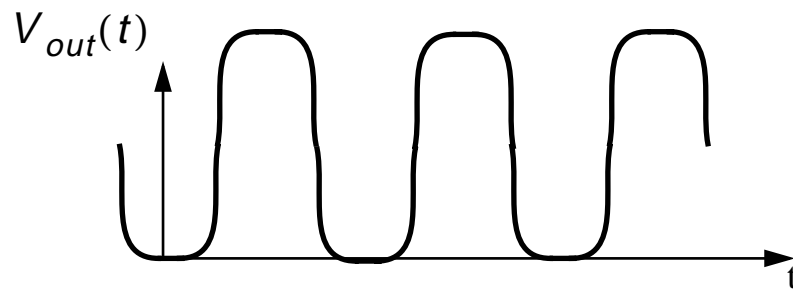
# Effect of Symmetry

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$$c_0 = \frac{1}{2\pi} \int_0^{2\pi} \Gamma(x) dx$$

Symmetric rise and fall time

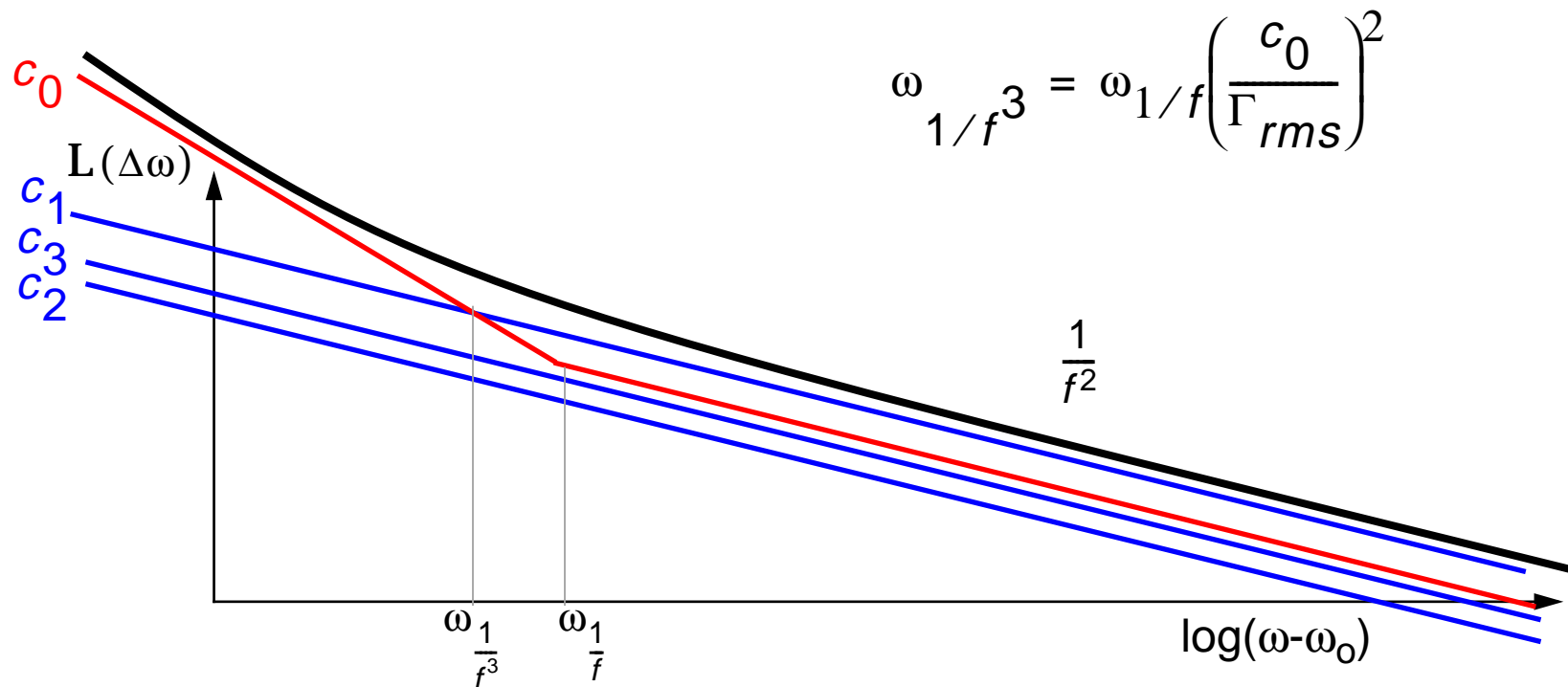
Asymmetric rise and fall time



*The dc value of the ISF is governed by rise and fall time symmetry, and controls the contribution of low frequency noise to the phase noise.*

# $1/f^3$ Corner of Phase Noise Spectrum

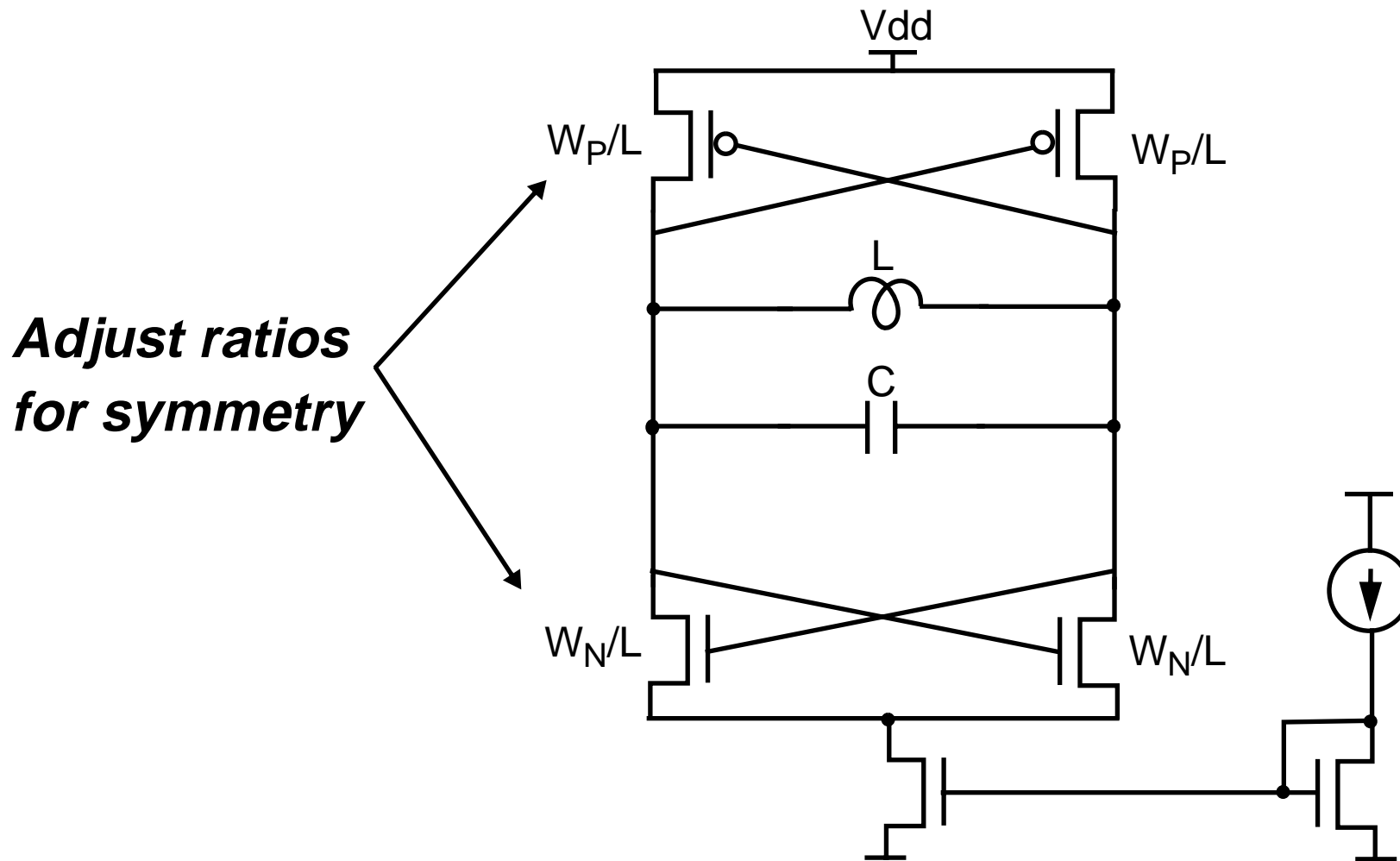
*The  $1/f^3$  corner of phase noise is NOT the same as  $1/f$  corner of device noise*



*By designing for a symmetric waveform, the performance degradation due to low frequency noise can be minimized.*

# A Symmetric LC Oscillator

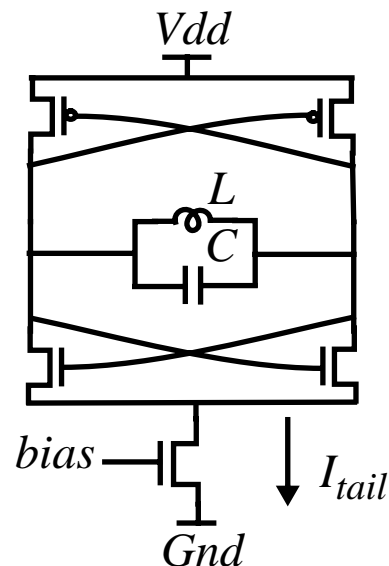
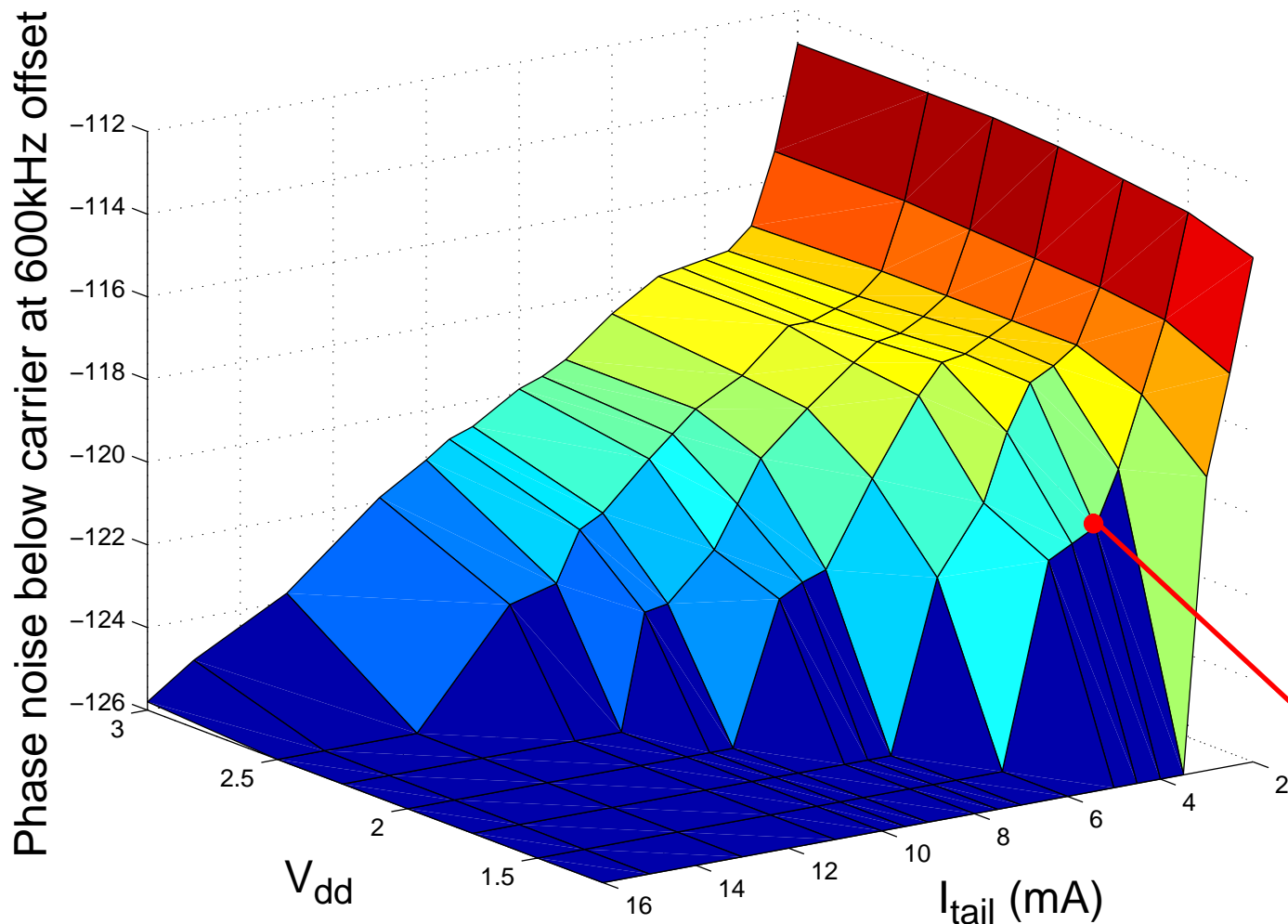
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***Possible to Adjust Symmetry Properties of the Waveform***

# Complementary Cross-Coupled VCO

$f_0=1.8\text{GHz}$ ,  $0.25\mu\text{m}$  Process

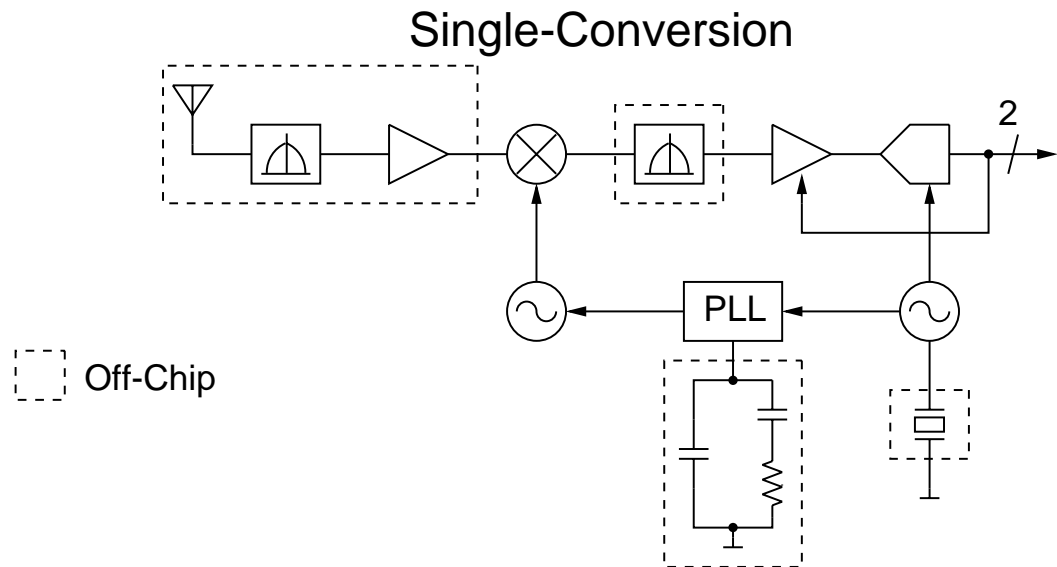
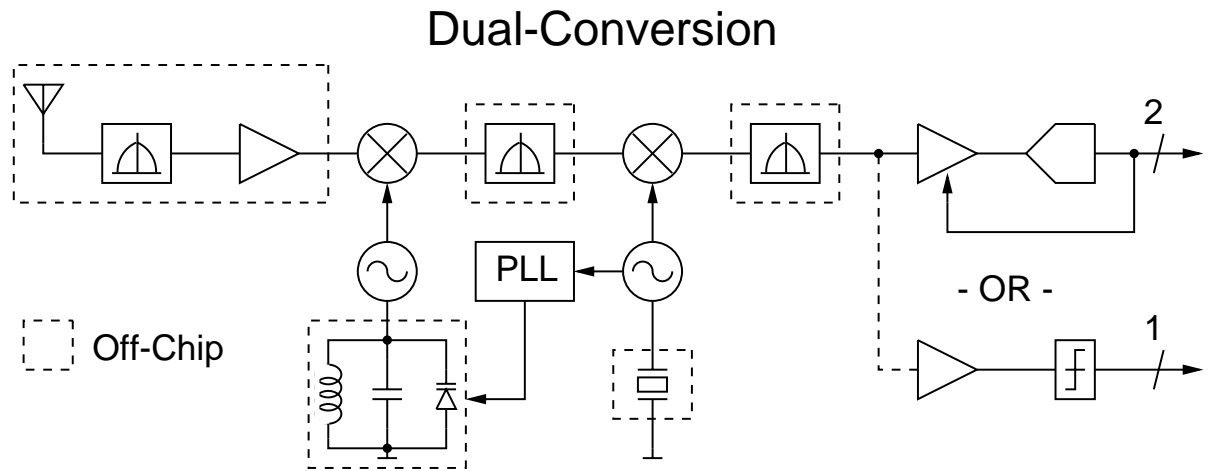


$f_0=1.8\text{GHz}$   
 $P=6\text{mW}$   
 $-121\text{dBc/Hz}@600\text{kHz}$

# GPS OVERVIEW: TYPICAL RECEIVER ARCHITECTURES

## Distinguishing Features:

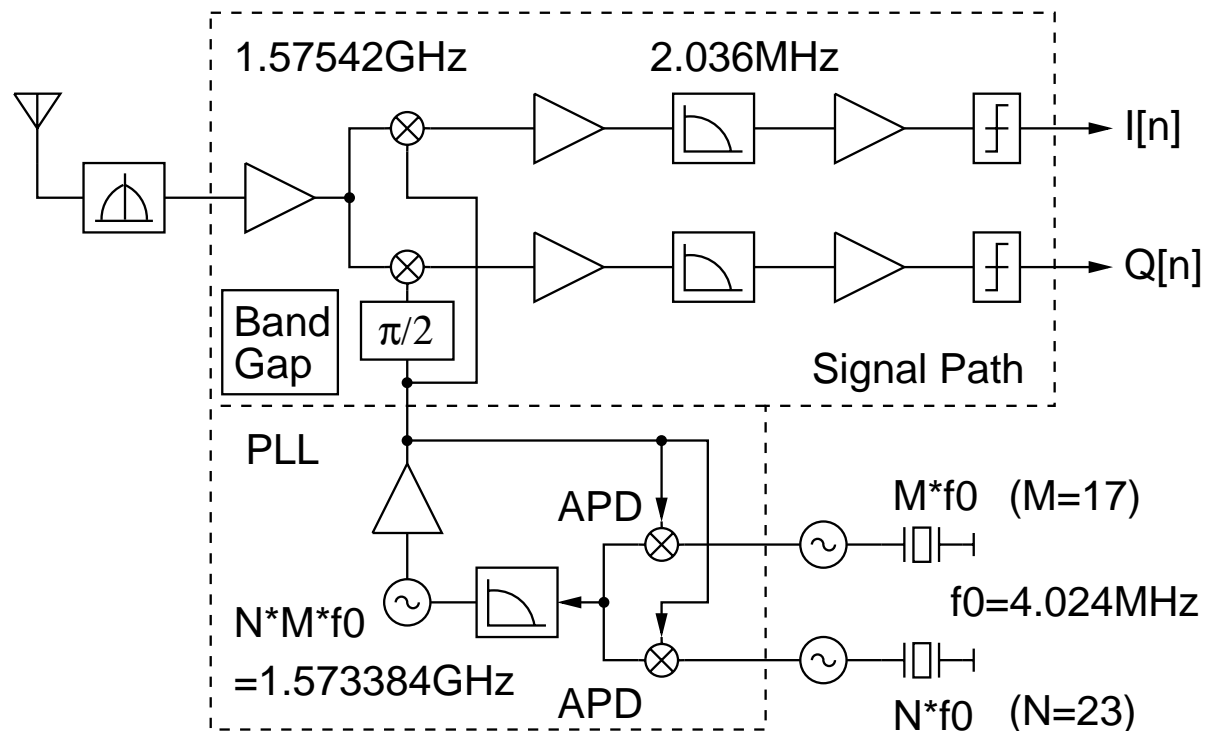
- Typical on-chip  $P_D$  is 100mW – 500mW
- Off-chip LNA or active antenna
- Off-chip IF filtering
- 1 or 2 bit quantization



# ARCHITECTURE: LOW-IF RECEIVER

Primary Goal: Make choices to minimize  $P_D$ , maximize integration.

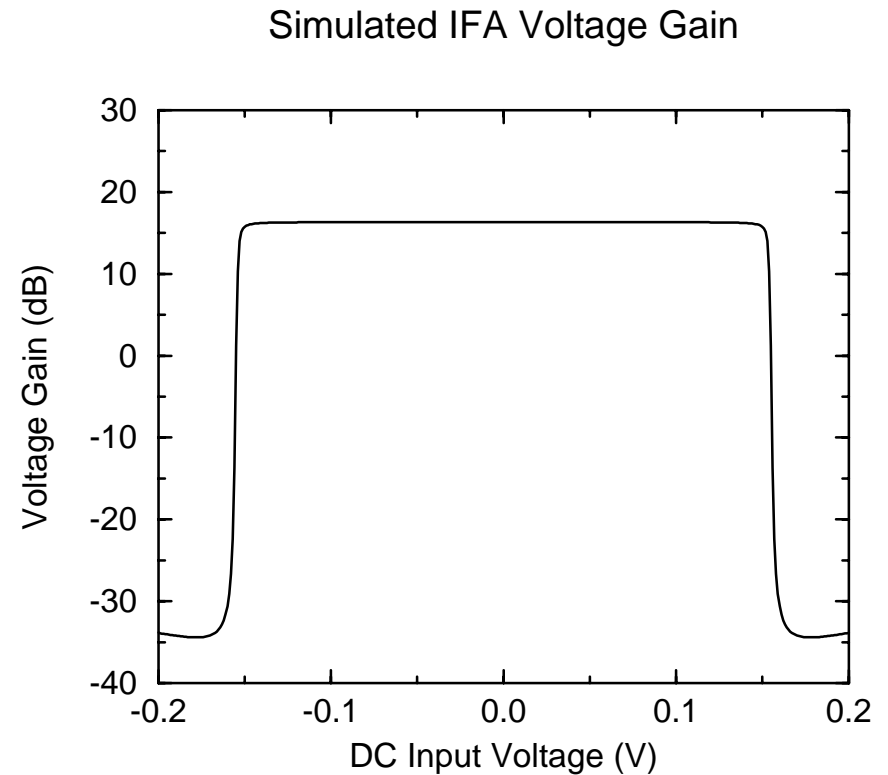
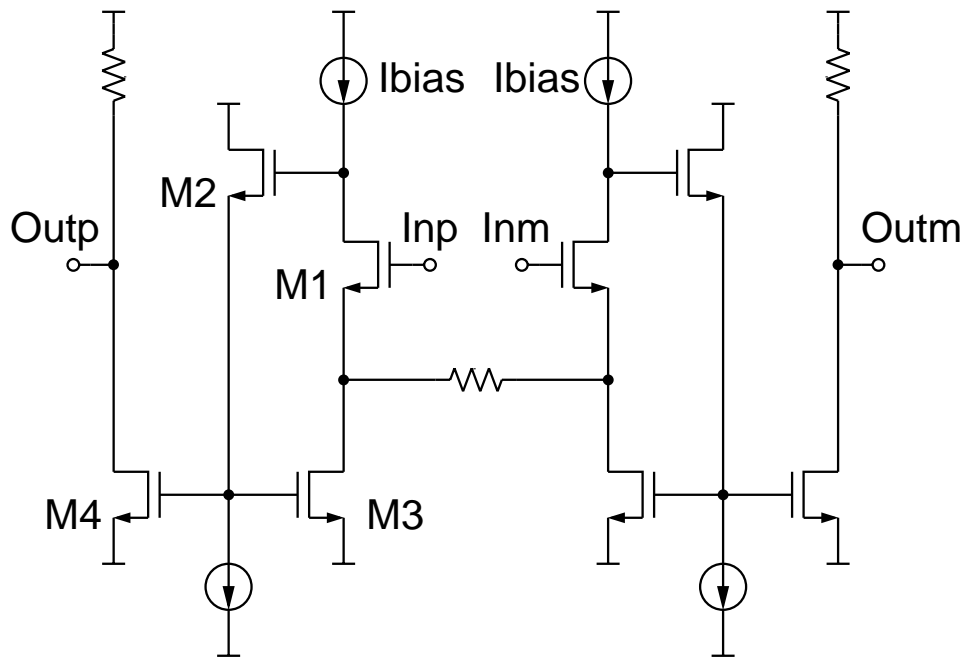
- Low-IF  $\Rightarrow$  On-chip active channel filter.
- Image in GPS band  $\Rightarrow$  Relaxed I/Q matching.
- Eliminate PLL prescaler  $\Rightarrow$  Saves power / noise.
- 1-bit quantization for simplicity.



# CIRCUITS: IFA

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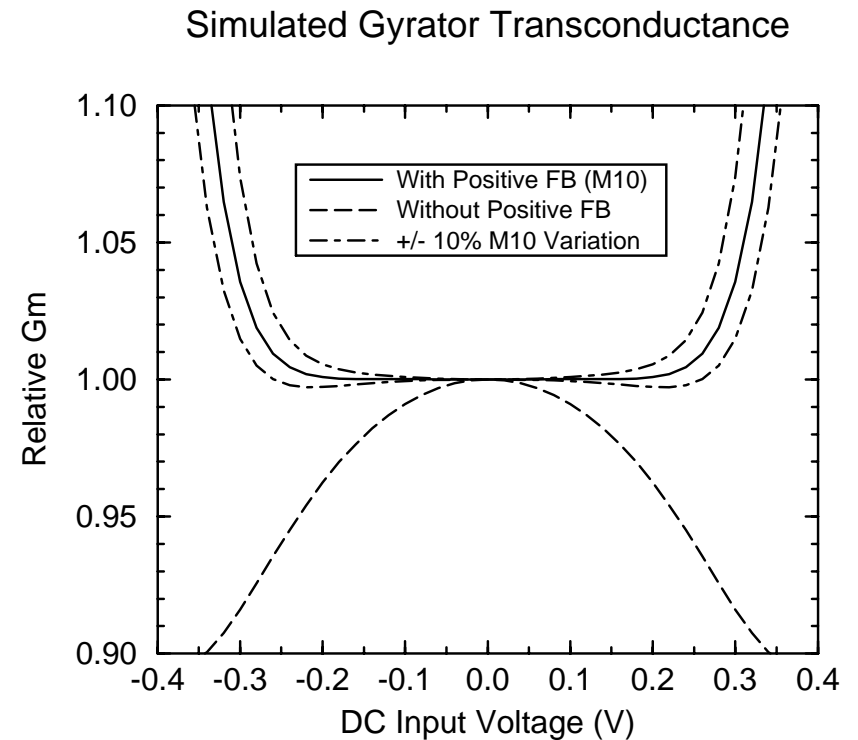
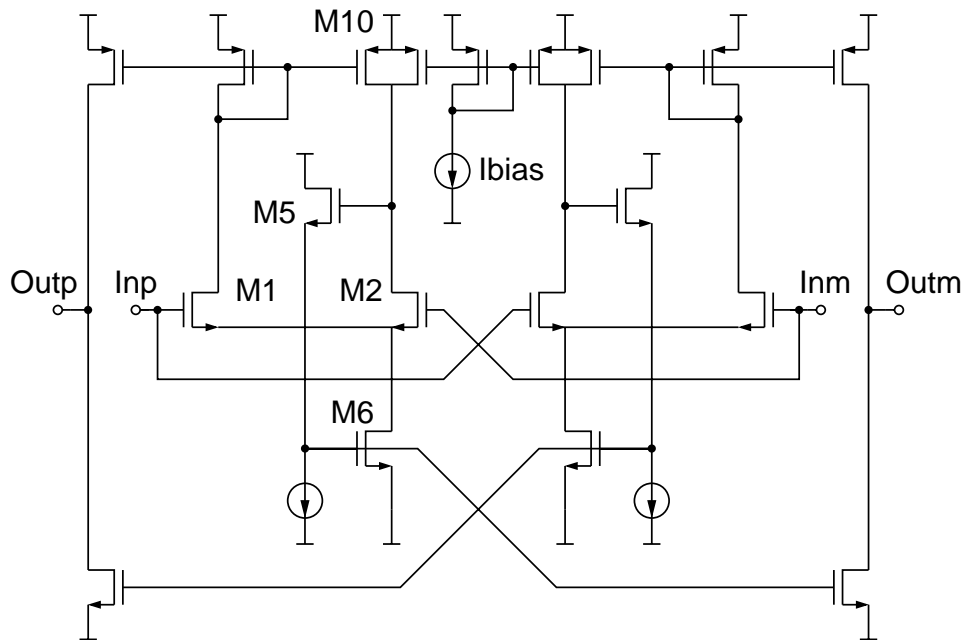
- Low input capacitance, high linearity.
- Load resistors terminate the active filter input.





# CIRCUITS: GM-C FILTER (TRANSCONDUCTOR)

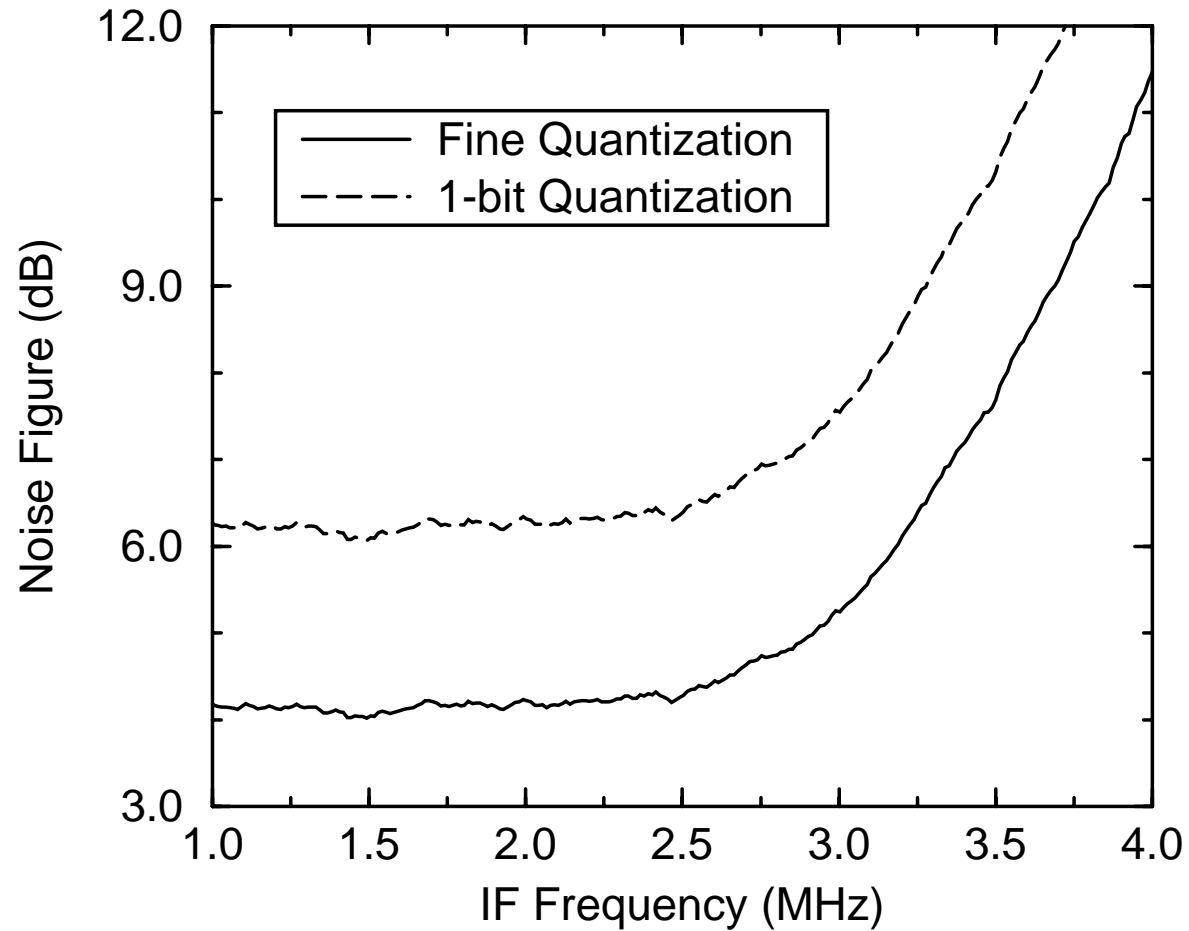
Use two *square-law* transconductors to build a *linear*, class-AB transconductor. A little positive feedback (M10) compensates for mobility degradation in M1.



# EXPERIMENTAL RESULTS: NOISE FIGURE

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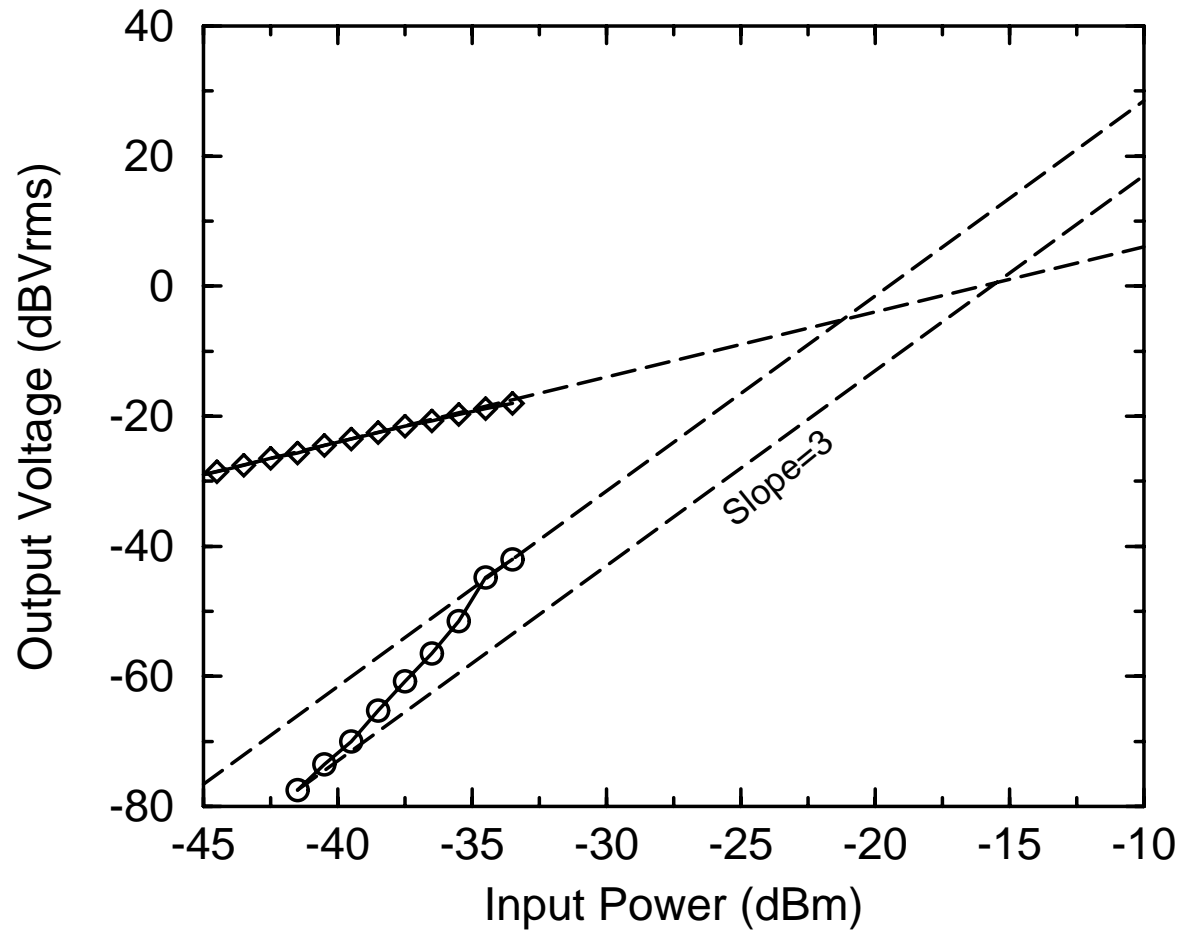
Coherent Receiver Spot Noise Figure  
(Pre-Limiter)



# EXPERIMENTAL RESULTS: LINEARITY

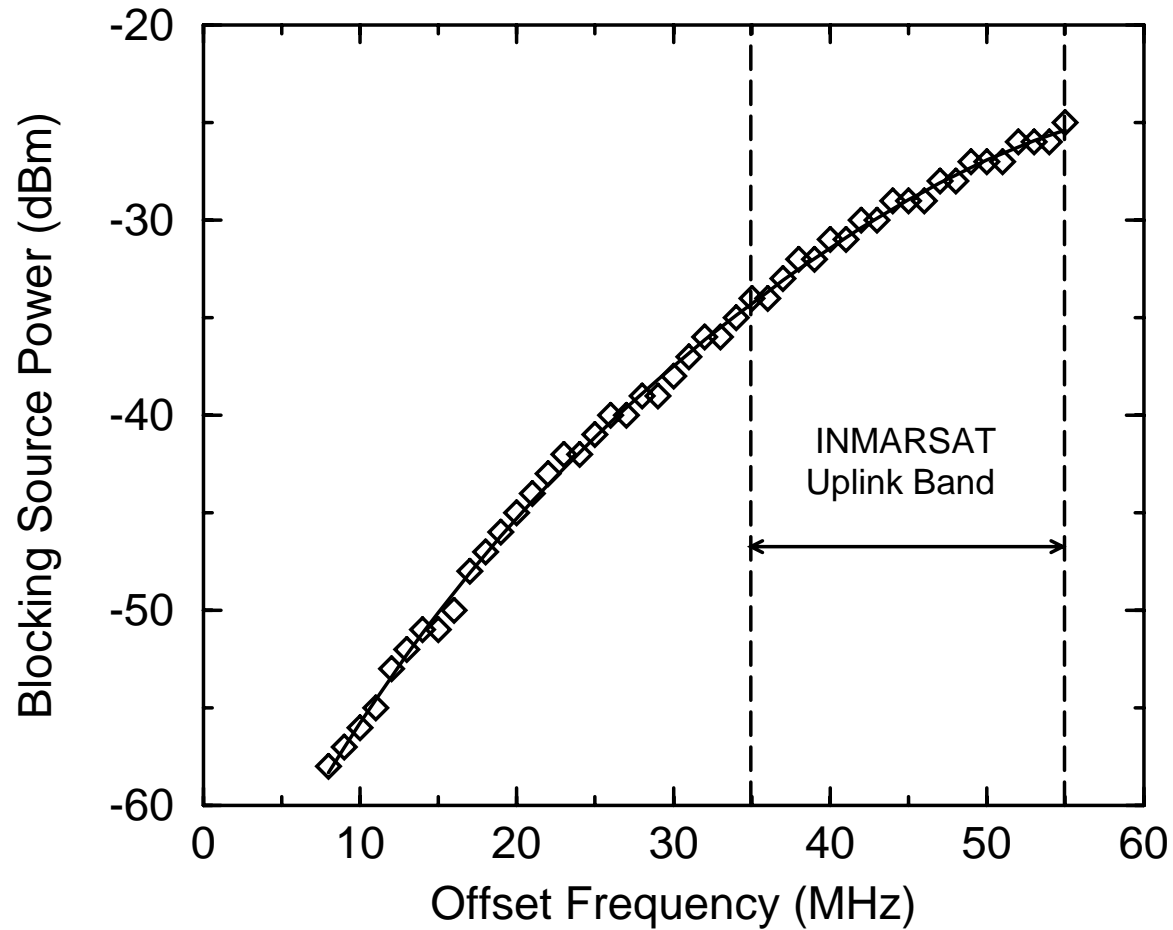
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## Signal Path 3rd Order Intermodulation



# EXPERIMENTAL RESULTS: BLOCKING PERFORMANCE

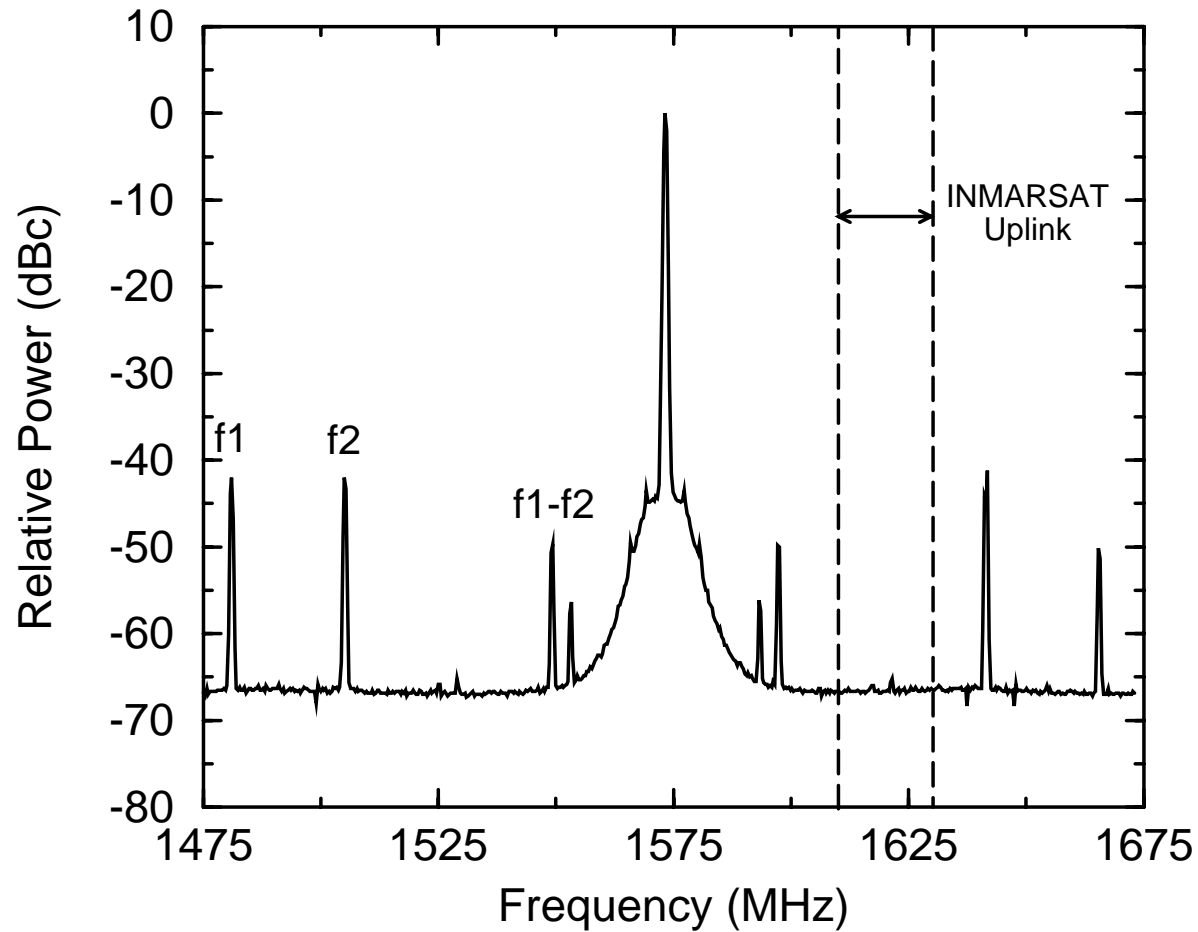
Receiver 1-dB Blocking De-Sensitization  
(No Front-End RF Filter)



# EXPERIMENTAL RESULTS: PLL SPURIOUS

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## PLL Spurious



# PERFORMANCE SUMMARY

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<i>Signal Path Performance</i>		<i>PLL Performance</i>	
LNA Noise Figure	2.4dB	Loop Bandwidth	5MHz
LNA S11	$\leq -15\text{dB}$	Spurious Tones	$\leq -42\text{dBc}$
Coherent Receiver NF	4.1dB	VCO Tuning Range	240MHz ( $\pm 7.6\%$ )
IIP3 (Filter-limited)	-16dBm @ -43dBm $P_s$	VCO Gain Constant	240MHz/V
Peak SFDR	57dB	LO Leakage @ LNA	$< -53\text{dBm}$
Filter Cutoff Freq.	3.5MHz		
Filter PB Peaking	$< 1\text{dB}$	<i>Power/Technology</i>	
Filter SB Atten.	$\geq 52\text{dB @ 8MHz}$ $\geq 68\text{dB @ 10MHz}$	Signal Path	79mW
Pre-Filter $G_p$	19dB	PLL / VCO	36mW
Pre-Filter $A_v$	32dB	Supply Voltage	2.5V
Total $G_p$	$\approx 82\text{dB}$	Die Area	$11.2\text{mm}^2$
Total $A_v$	$\approx 107\text{dB}$	Technology	0.5 $\mu\text{m}$ CMOS
Non-Coherent Output SNR	15dB		

# Closing Thoughts

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- ❑ **CMOS is not ideal, but much more than adequate for many applications.**
- ❑ **Scaling trends will continue to improve CMOS.**
- ❑ **“RF CMOS” is not an oxymoron anymore.**

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